



Active pixel sensors in 180 nm HV CMOS technology for HL-LHC detector upgrades

Daniel Muenstermann

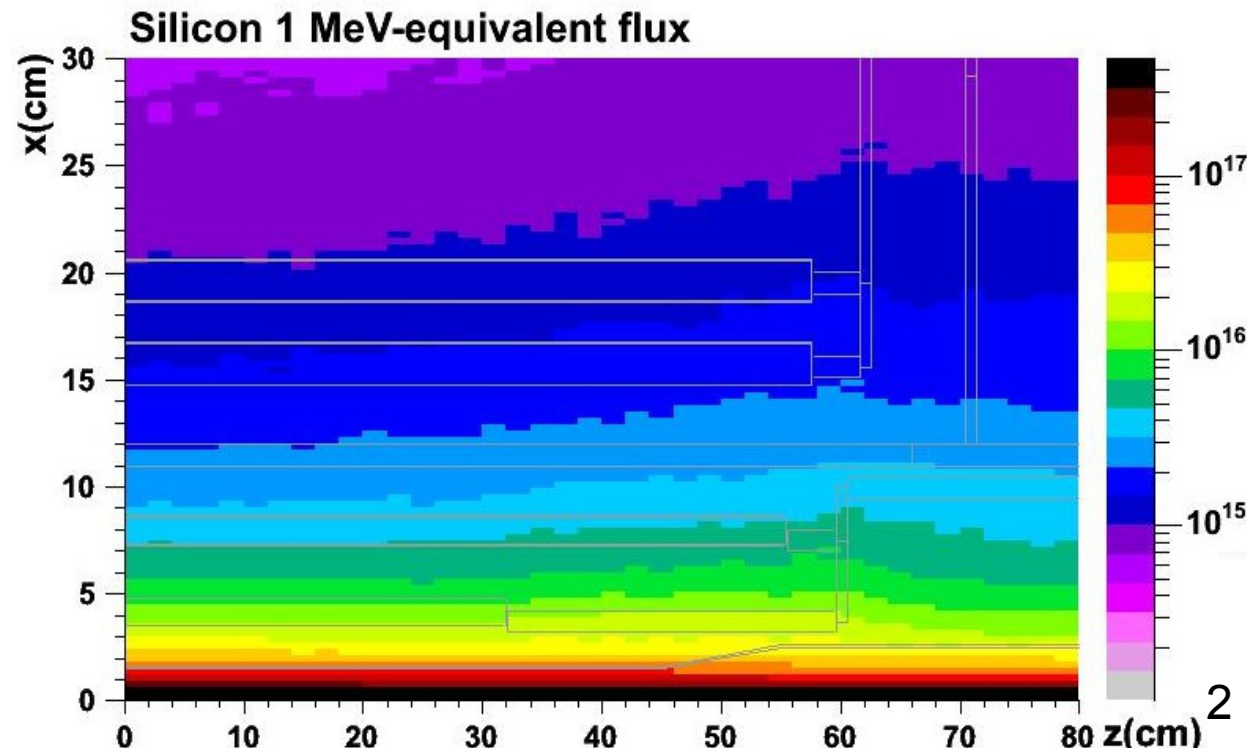
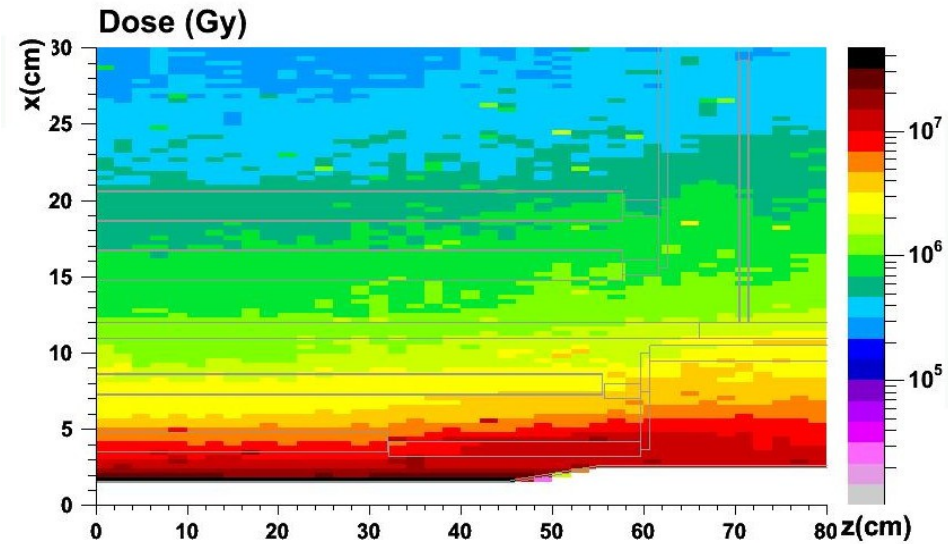
on behalf of the participating institutes:

*U Bonn, CERN, CPPM Marseille, U Geneva,
U Glasgow, U Heidelberg, LBNL*



Fluences at HL-LHC

- integrated luminosity: 3000 fb^{-1}
- including a safety factor of 2 to account for all uncertainties this yields for ATLAS:
 - at 5 cm radius:
 - $\sim 2 \cdot 10^{16} \text{ n}_{\text{eq}} \text{ cm}^{-2}$
 - $\sim 1500 \text{ MRad}$
 - at 25 cm radius
 - up to $10^{15} \text{ n}_{\text{eq}} \text{ cm}^{-2}$
 - $\sim 100 \text{ MRad}$
 - several m^2 of silicon
- strip region
 - some $10^{14} \text{ n}_{\text{eq}} \text{ cm}^{-2}$
 - up to $\sim 200 \text{ m}^2$ of silicon





Implications

- High fluences: trapping dominant
 - reduce drift distance, increase field → reduce drift time:
 - thin planar, 3D sensors
- Large areas: low cost of prime importance
 - industrialised processes
 - large wafer sizes
 - cheap interconnection technologies
- **Idea: explore industry standard CMOS processes as sensors**
 - commercially available by variety of foundries
 - large volumes, more than one vendor possible
 - 8" to 12" wafers
 - low cost per area
 - (partially too) low resistivity p-type Cz silicon
 - thin active layer
 - wafer thinning possible (down to 75 μm is standard, even less is possible)

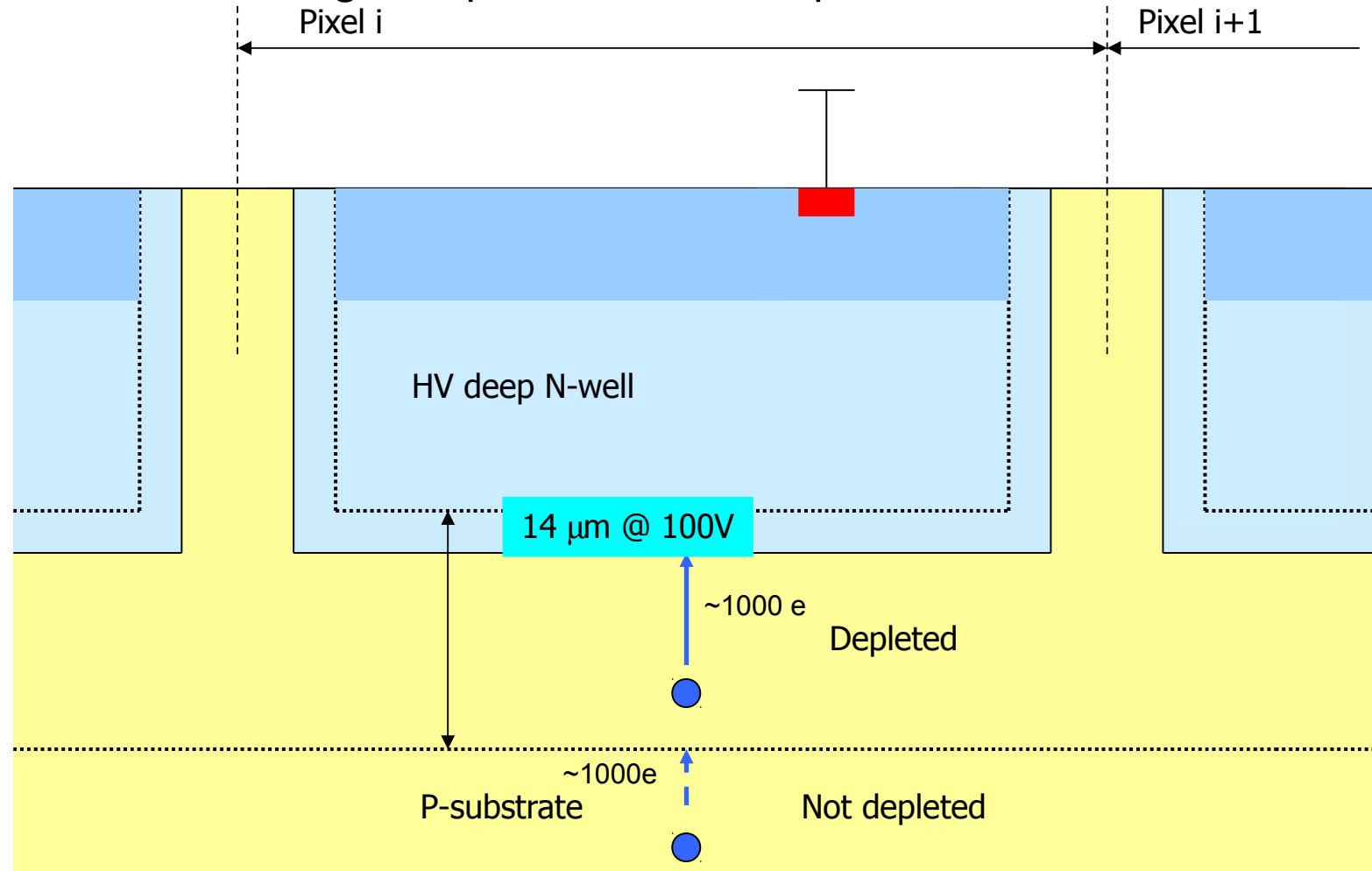


CMOS? Which flavours?

- Identified 3 main branches with several mixtures:
 - passive n-in-p planar sensors produced on 8" wafers
 - HV-CMOS active sensors
 - HR-CMOS active sensors/MAPS
- n-in-p planar sensors done by CMOS foundries
 - thanks to CMOS imaging sensors many foundries now offer
 - high-resistivity 8" p-bulk substrates
 - sensor thinning and post-thinning backside processing – but reticule-based
 - significantly lower cost for larger volumes
 - should be in general suitable for n-in-p sensors, but
 - unprecedented bias voltages to be applied → guard rings?
 - inter-pixel isolation: p-wells=p-stops? p-spray?
 - past and planned projects
 - apparently, there were already unsuccessful trials...
 - ATLAS plans to try again
 - key question likely to be implant profiles, p-stops and stitching

A HV-CMOS sensor...

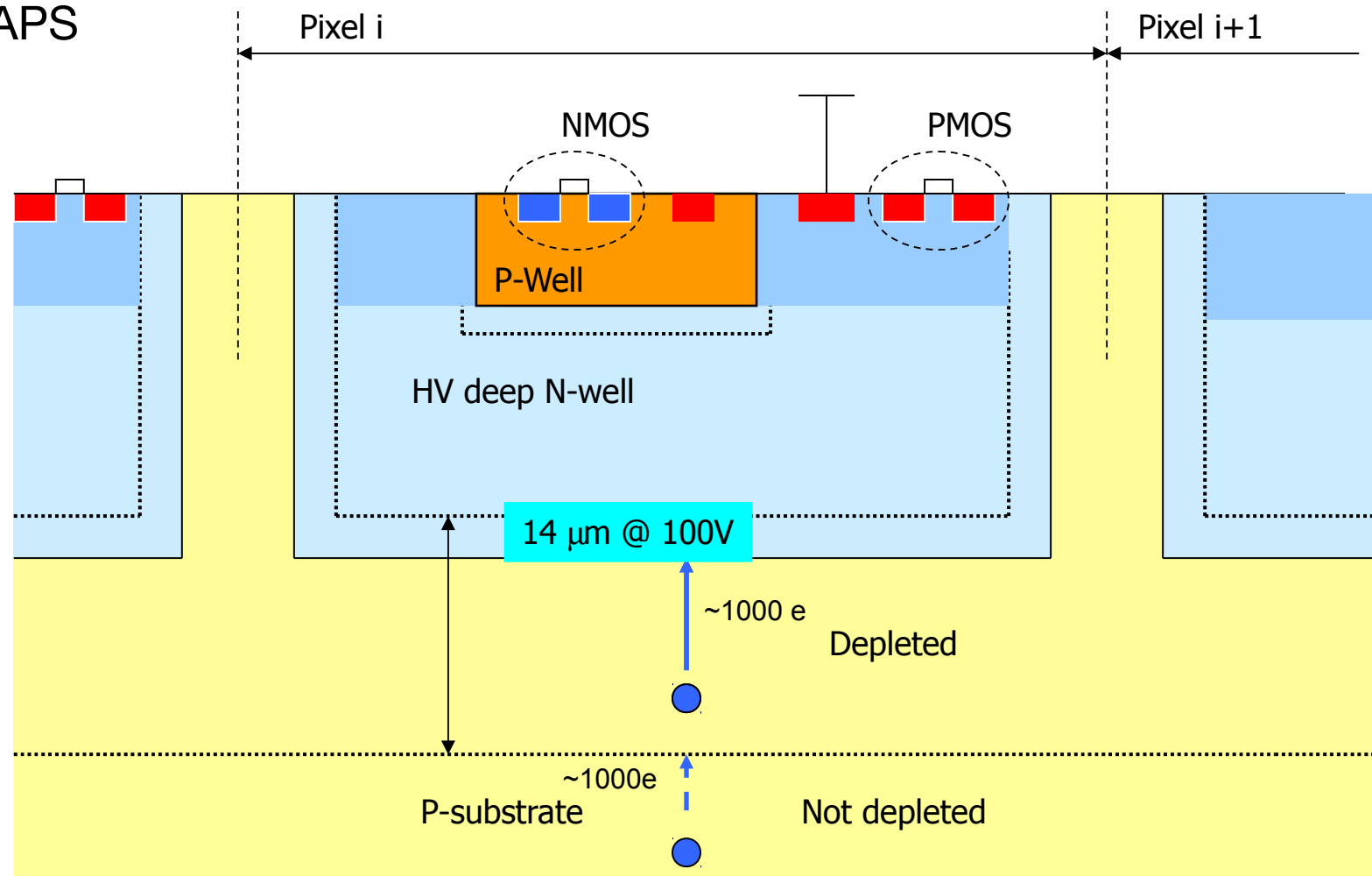
- essentially a standard n-in-p sensor
- depletion zone 10-20 μm : signal in the order of 1-2ke⁻
 - quite challenging for hybrid pixel readout electronics
 - HR-CMOS would have larger depletion zone → “passive CMOS sensors”



The depleted high-voltage diode used as sensor (n-well in p-substrate diode)

...including active circuits: *smart diode array (SDA)*

- implementation of
 - first amplifier stages → most simple approach, e.g. Time/CLICpix
 - additional circuits: discriminators, impedance converters, logic, ...
 - still avoids crosstalk by clock networks
 - finally: MAPS



CMOS electronics placed inside the diode (inside the n-well)

Prototypes

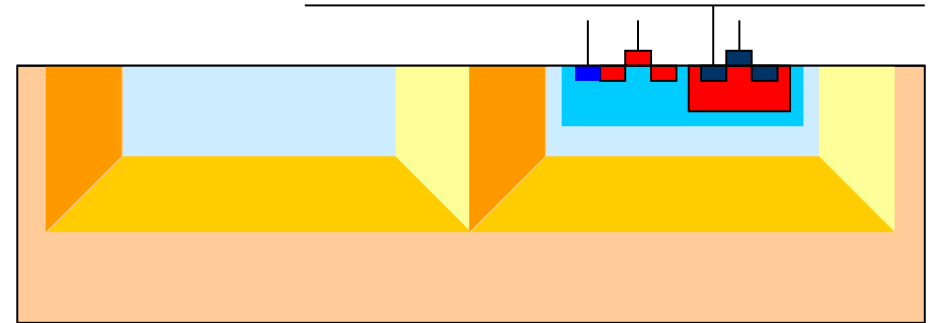
- Several test-chips already existing, see backup slides for more detailed results

SDA with sparse readout
("intelligent" CMOS pixels)
HV2/MuPixel chip

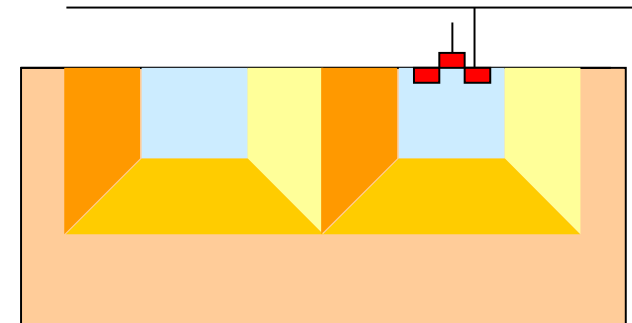
SDA with frame readout
(simple PMOS pixels)
HVM chip

SDA with capacitive readout
("intelligent" pixels)
Capacitive coupled pixel
detectors
CCPD1 and CCPD2 detectors

Binary information

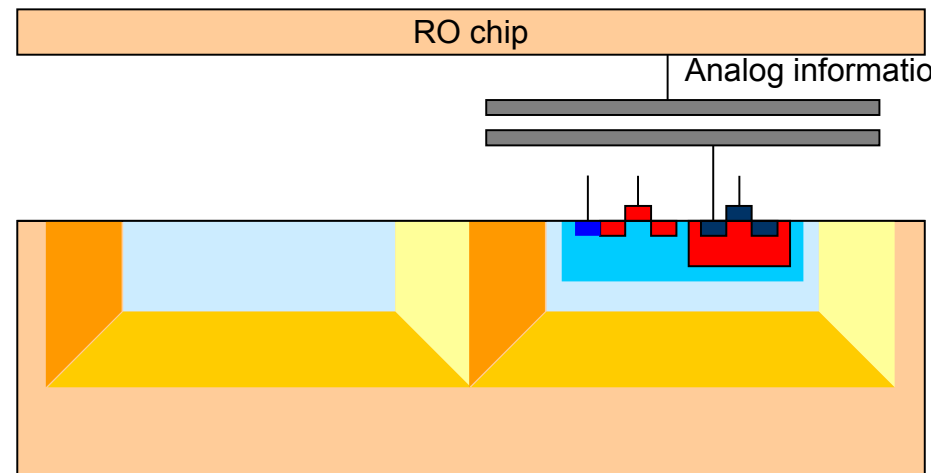


Analog information



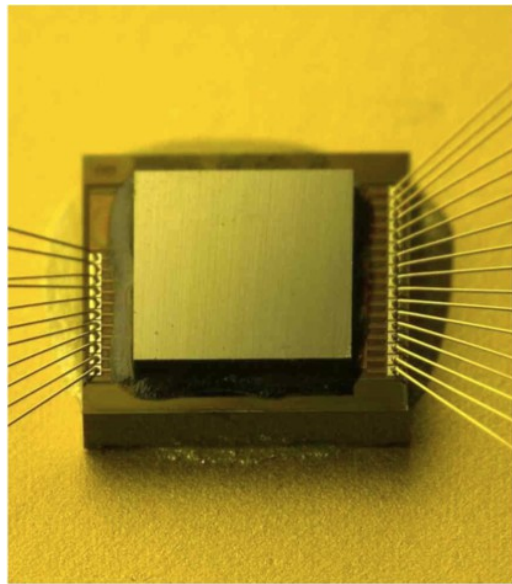
RO chip

Analog information





Prototype summaries



First chip – CMOS pixels
 Hit detection in pixels
 Binary RO
 Pixel size 55x55µm
 Noise: 60e
 MIP seed pixel signal 1800 e
 Time resolution 200ns

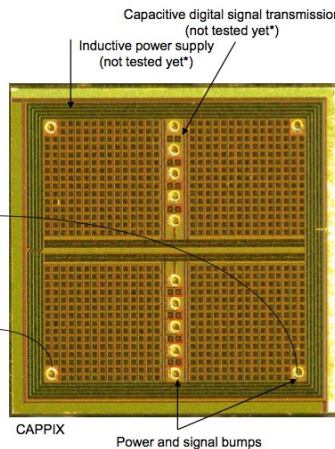
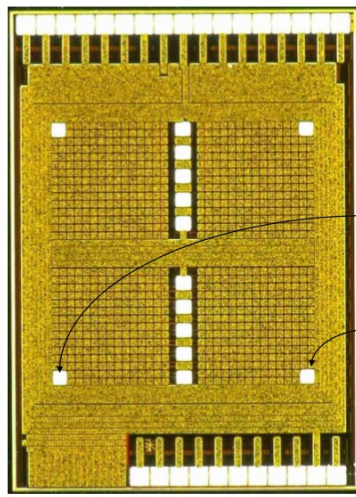
Bumpless hybrid detector
CCPD1 Chip
 Bumpless hybrid detector
 Based on capacitive chip to chip
 signal transfer
 Pixel size 78x60µm
 RO type: capacitive
 Noise: 80e
 MIP signal 1800e

Frame readout - monolithic
PM1 Chip
 Pixel size 21x21µm
 Frame mode readout
 4 PMOS pixel electronics
 128 on chip ADCs
 Noise: 90e
 Test-beam: MIP signal 2200e/1300e
 Efficiency > 85% (timing problem)
 Spatial resolution 7µm
 Uniform detection

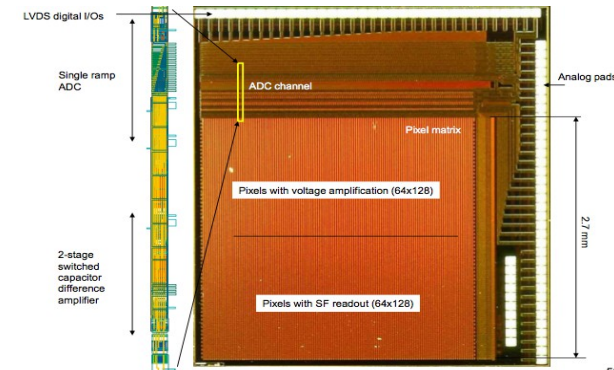
CCPD2 Chip
 Edgeless CCPD
 Pixel size 50x50µm
 Noise: 30-40e
 Time resolution 300ns
SNR 45-60

PM2 Chip
 Noise: 21e (lab) - 44e (test beam)
Test beam: Detection efficiency 98%
Seed Pixel SNR ~ 27
Cluster Signal/Seed Pixel Noise ~ 47
Spatial resolution ~ 3.8 µm

Irradiations of test pixels
60MRad – SNR 22 at 10C (CCPD1)
 $10^{15} n_{eq}/cm^2$ – SNR 50 at 10C (CCPD2)



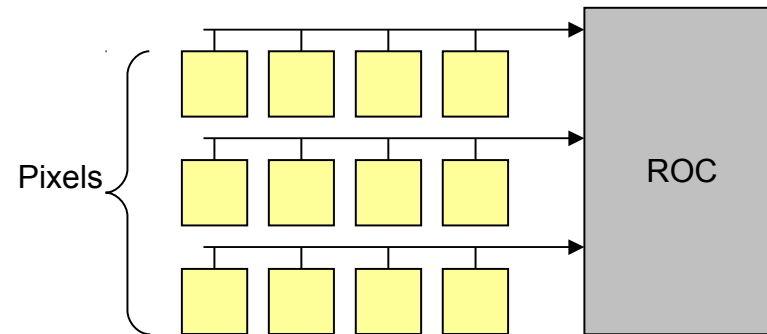
*If work, these features would allow to operate the readout chip without any mechanical contact



I. Peric

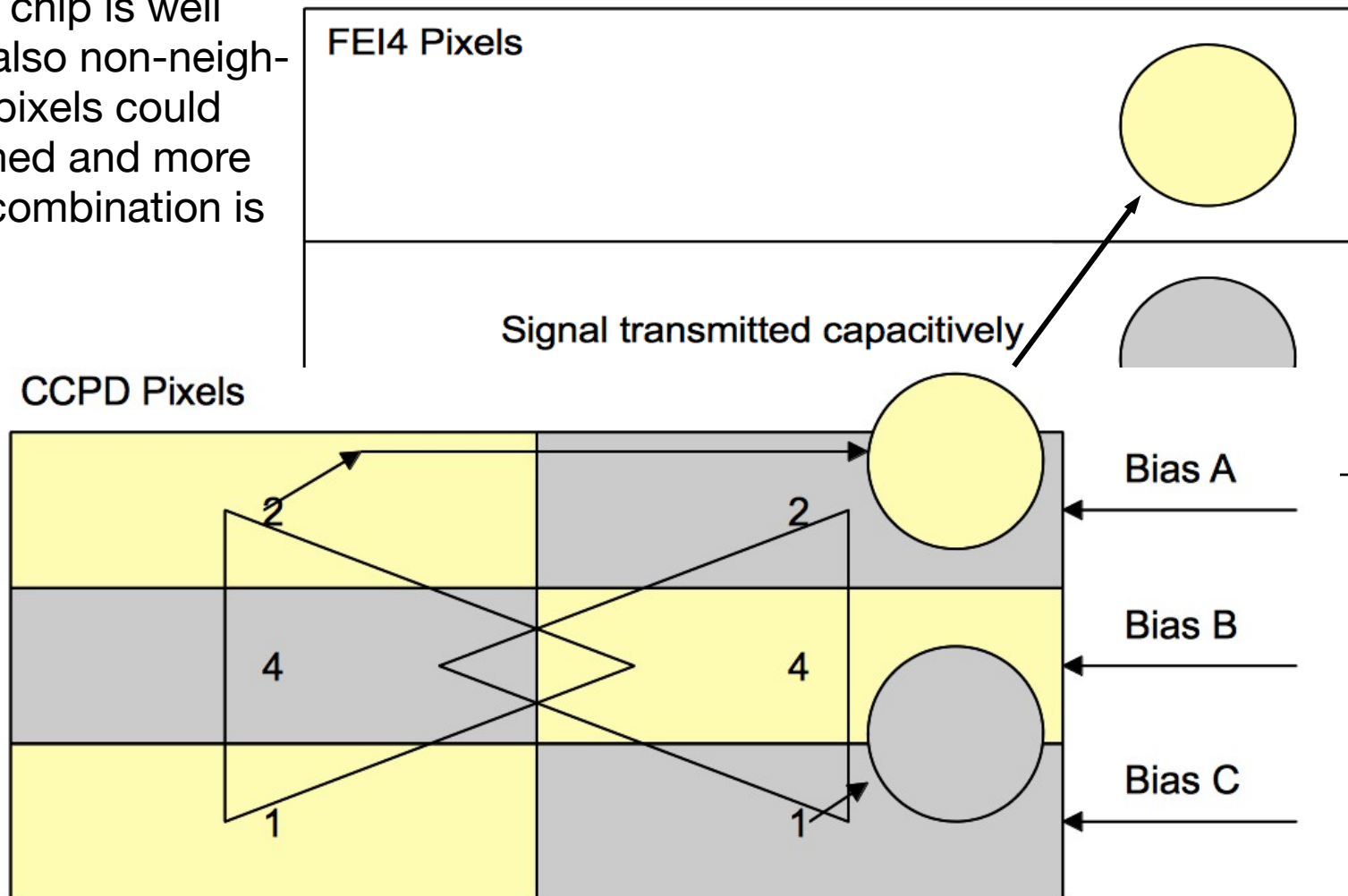
From MAPS to active sensors

- Existing prototypes would not be suitable for HL-LHC, mainly because
 - readout too slow
 - time resolution not compatible with 40 MHz operation
 - high-speed digital circuits might affect noise performance
- Idea: use HV-CMOS as sensor in combination with existing readout technology
 - fully transparent, can be easily compared to other sensors
 - can be combined with several readout chips
 - makes use of highly optimised readout circuits
 - can be seen as first step towards a sensor being integrated into a 3D-stacked readout chip (not only analogue circuits but also charge collection)
- Basic building blocks: *small* pixels (low capacitance, low noise)
 - can be connected in any conceivable way to match existing readout granularity, e.g.
 - (larger) pixels
 - strips



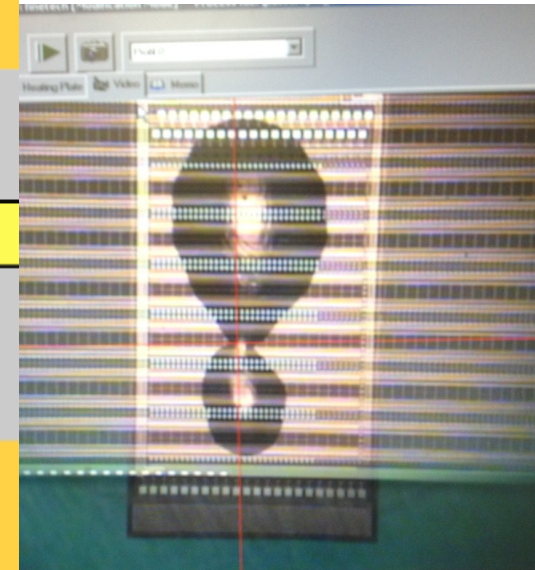
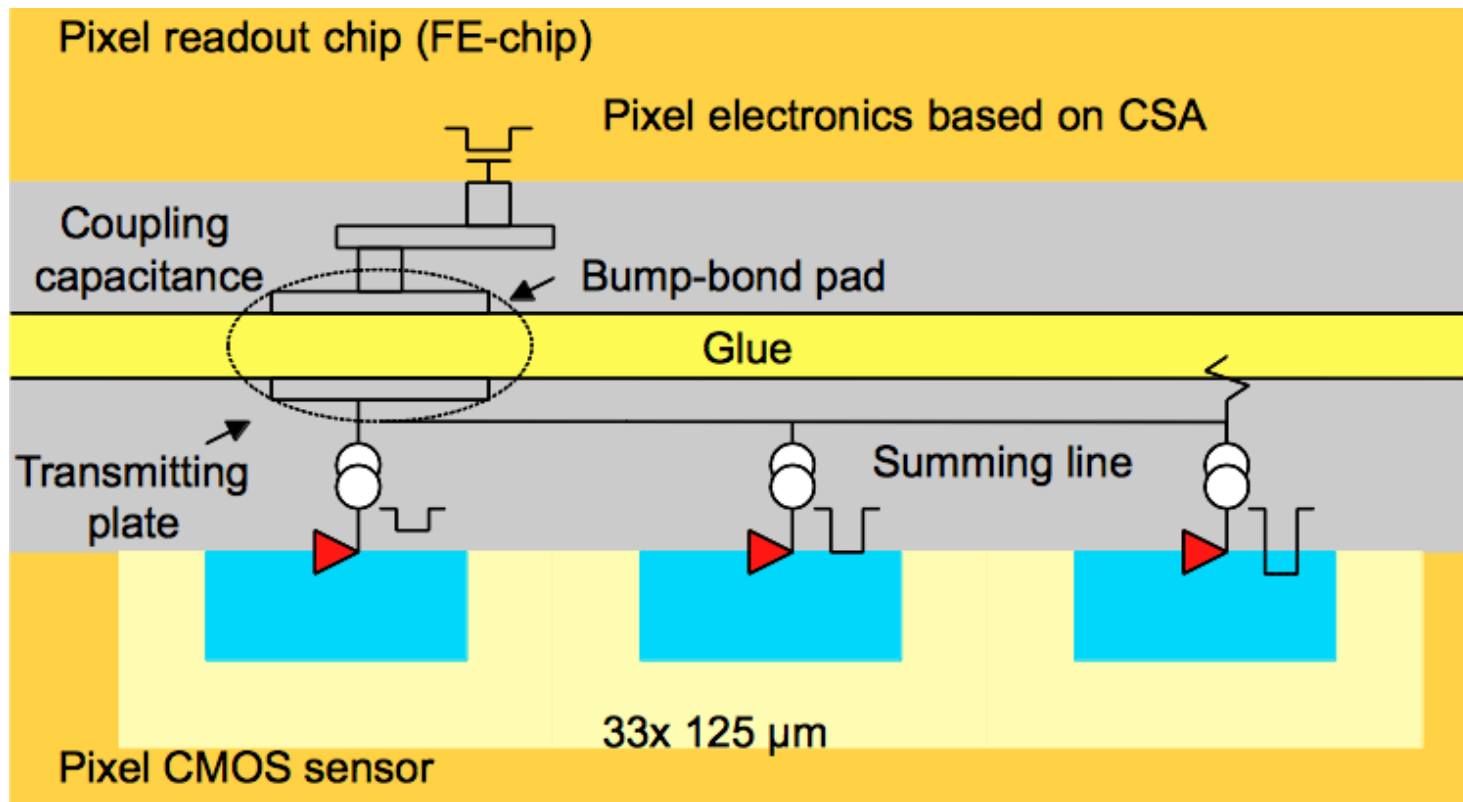
Pixels: sizes and combinations

- Possible/sensible pixel sizes: 20x20 to 50x125 μm
 - 50x250 μm (current ATLAS FE-I4 chip) too large
 - combine several sensor “sub-pixels” to one ROC-pixel
 - sub-Pixels encode their address/position into the signal as pulse-height-information instead of signal proportional to collected charge
 - routing on chip is well possible, also non-neighbour sub-pixels could be combined and more than one combination is possible



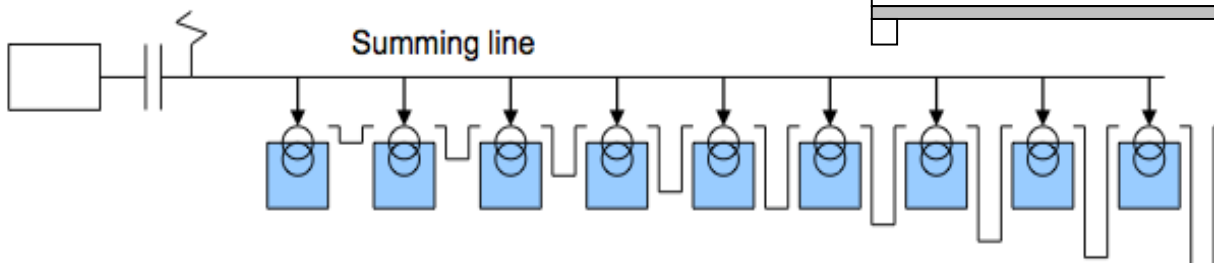
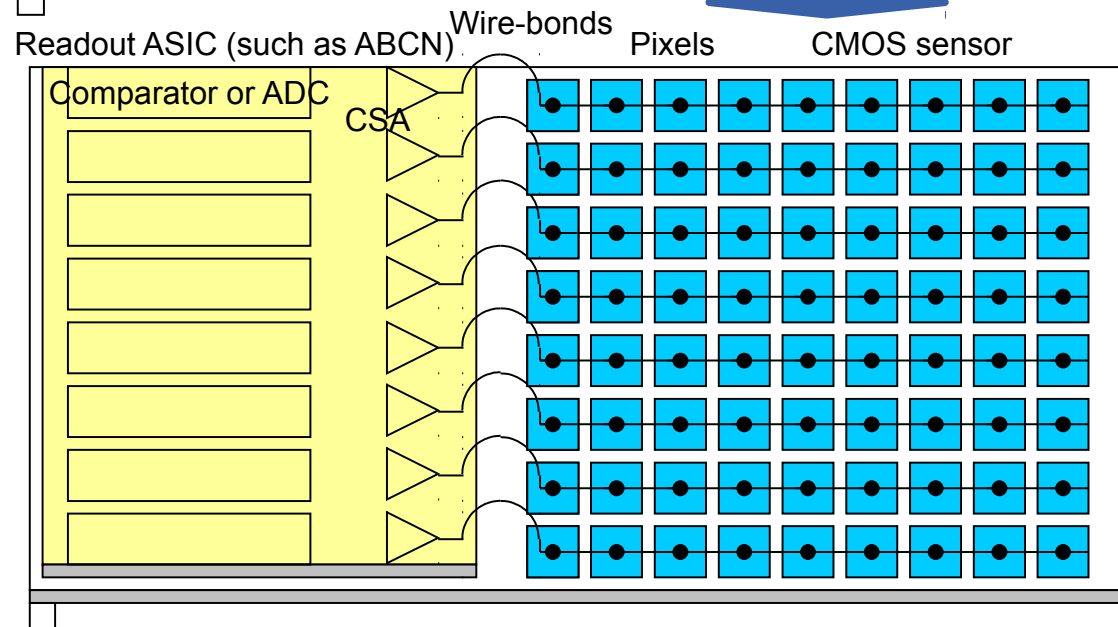
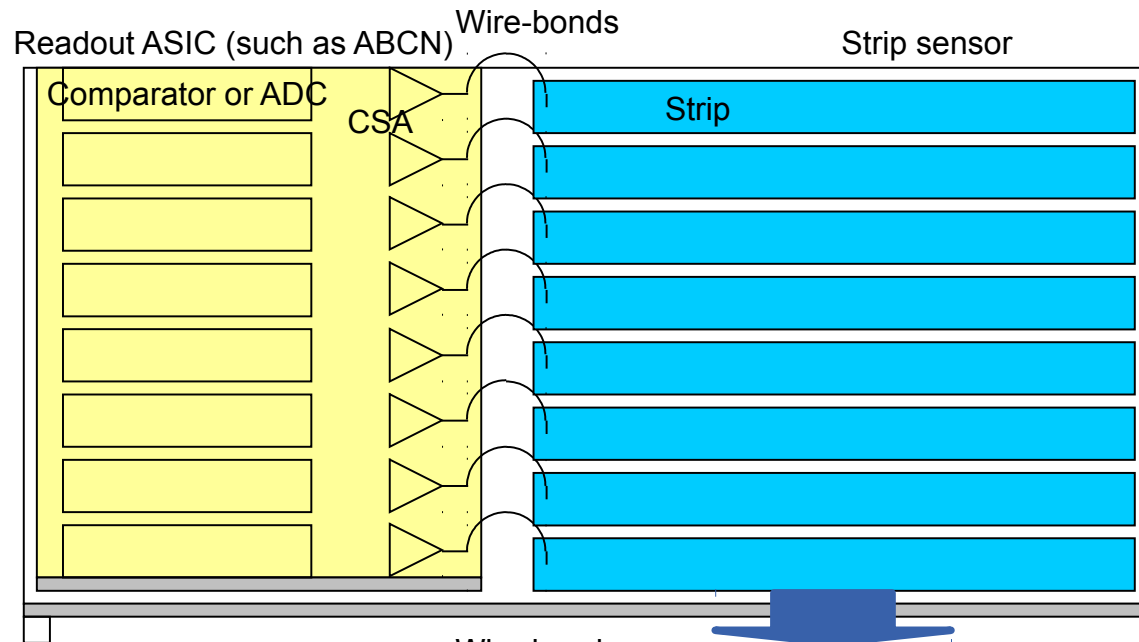
Pixels: bonding?

- Only reason not to use AC coupling with pixel sensors up to now was small coupling capacitance in association with low signal
 - amplification possible, hence AC transmission not a problem at all
 - allows to get rid of costly bump-bonding
 - layer thicknesses below $5\ \mu\text{m}$ have been reached with industry standard flip-chipping machines and rad-hard liquid epoxy glues
 - variations in glue thickness can be handled by tuning procedures and offline corrections if necessary



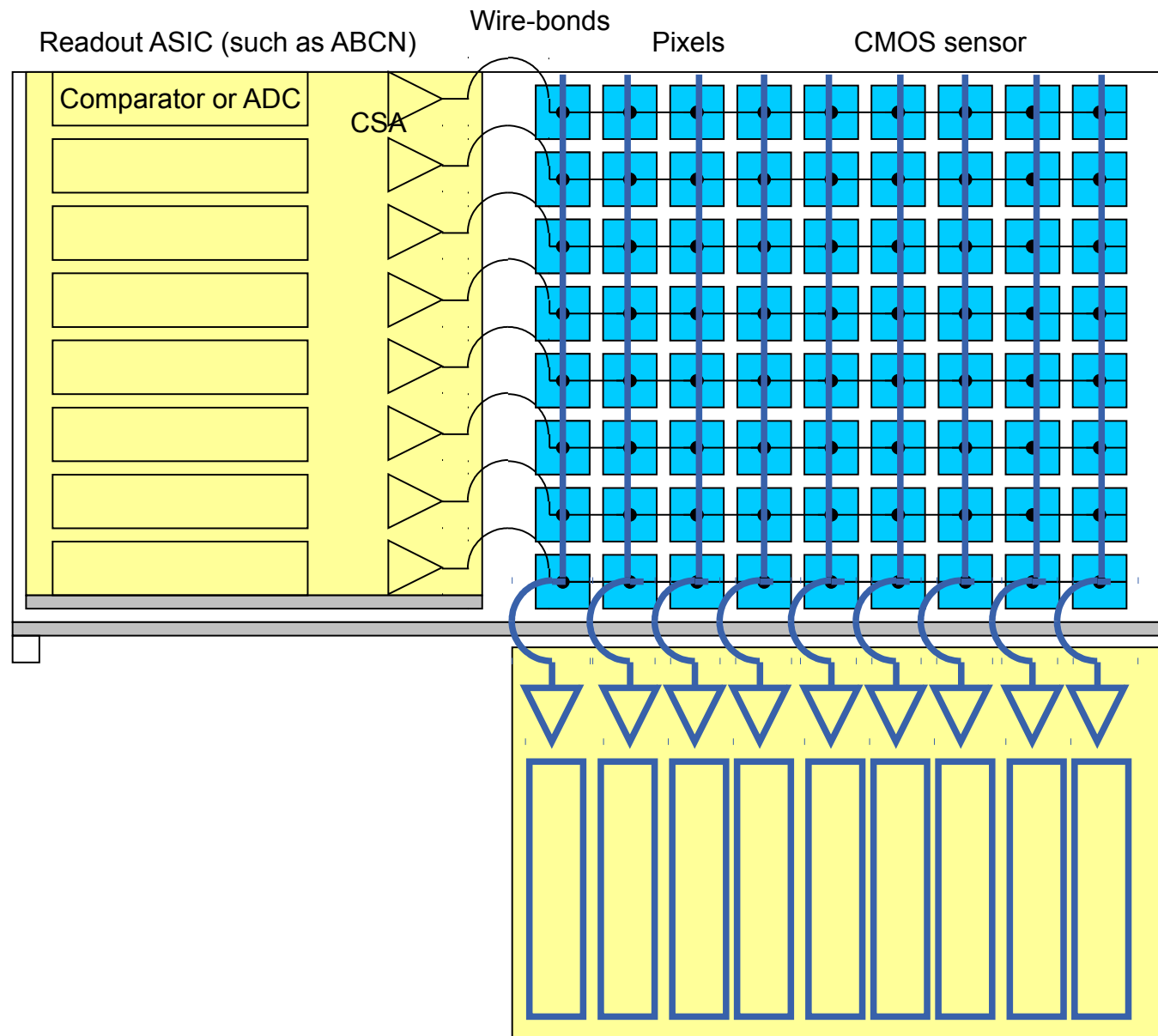
Strips

- Easiest idea would be to simply sum all pixels within a virtual strip
- Hit position along the strip can be again encoded by pulse height for analogue readout chips (e.g. Beetle)



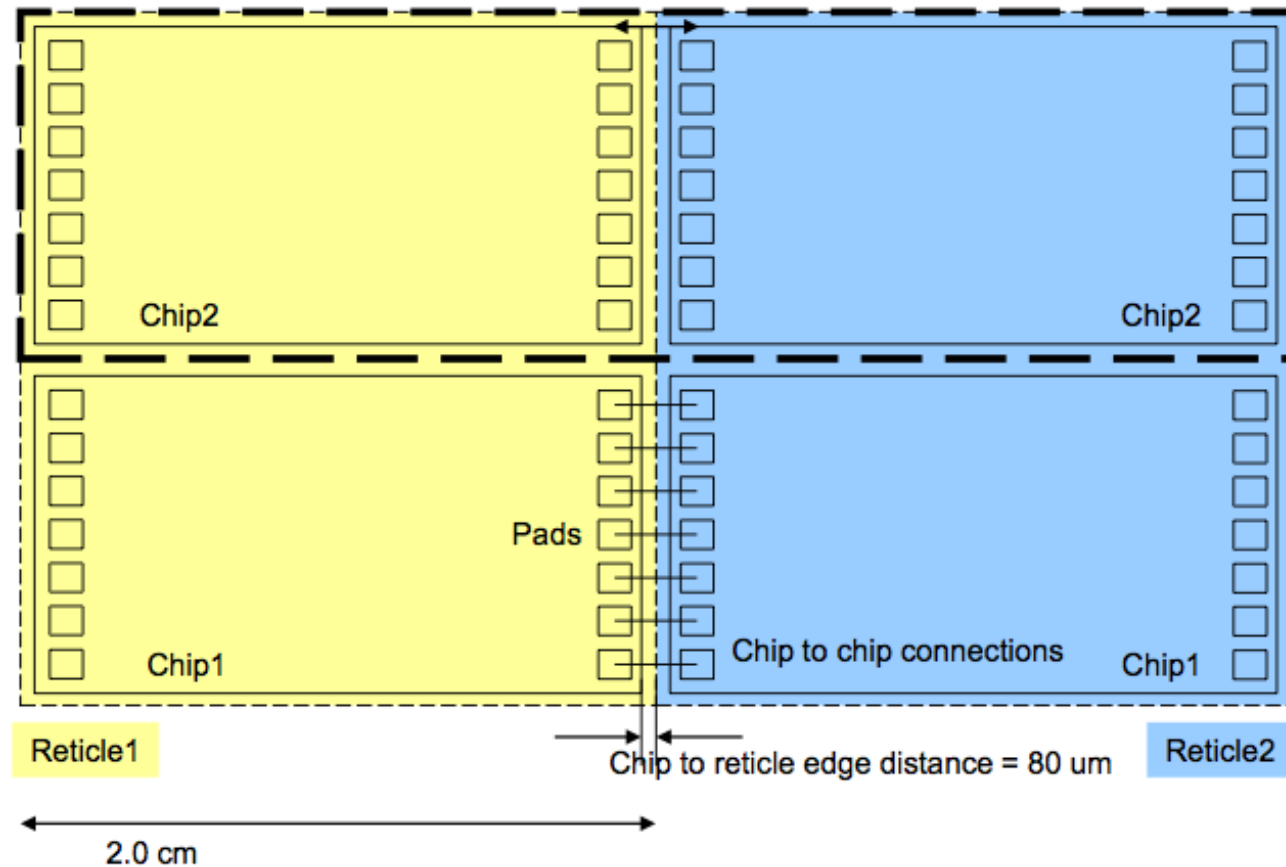
Strips

- Signals are digital so multiple connections are possible, e.g.
 - “crossed strips”
 - strips with double length but only half the pitch in r-phi



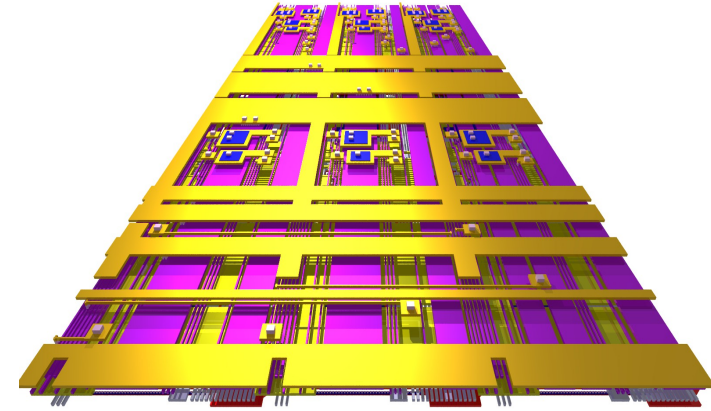
Reticule size/stitching

- Sensor size is currently limited by reticule size of ~2x2 cm
 - however, the yield should be good (very simple circuit, essentially no “central” parts) so it might be interesting to cut large arrays of sensors from a wafer and connect individual reticules by
 - wire-bonding
 - post-processing (one metal layer, large feature size)
- There are HV-CMOS processes/foundries which allow for stitching
- Very slim dicing streets
 - Gaps between 1-chip modules could be rather narrow



AMS H18 HV-CMOS

- Project initiated by Ivan Peric (U Heidelberg)
- Austria Micro Systems offers HV-CMOS processes with 180 nm feature size in cooperation with IBM
 - biasing of substrate to ~60-100V possible
 - substrate resistivity $\sim 20 \text{ Ohm} \cdot \text{cm} \rightarrow N_{\text{eff}} > 10^{14}/\text{cm}^3$
 - radiation induced N_{eff} insignificant even for innermost layers
 - depletion depth in the order of 10-20 $\mu\text{m} \rightarrow \text{signal} \sim 1\text{-}2 \text{ ke}^-$
 - on-sensor amplification possible - and necessary for good S/N
 - key: small pixel sizes \rightarrow low capacitance \rightarrow low noise
 - additional circuits possible, e.g. discriminator
 - beware of 'digital' crosstalk
 - full-sized radiation hard drift-based MAPS feasible, but challenging
 - aim for 'active sensors' in conjunction with rad-hard readout electronics first
 - parallel project: MAPS for the m3e experiment at PSI, uses very similar analogue circuits, monolithic readout





ATLAS HV-CMOS R&D collaboration

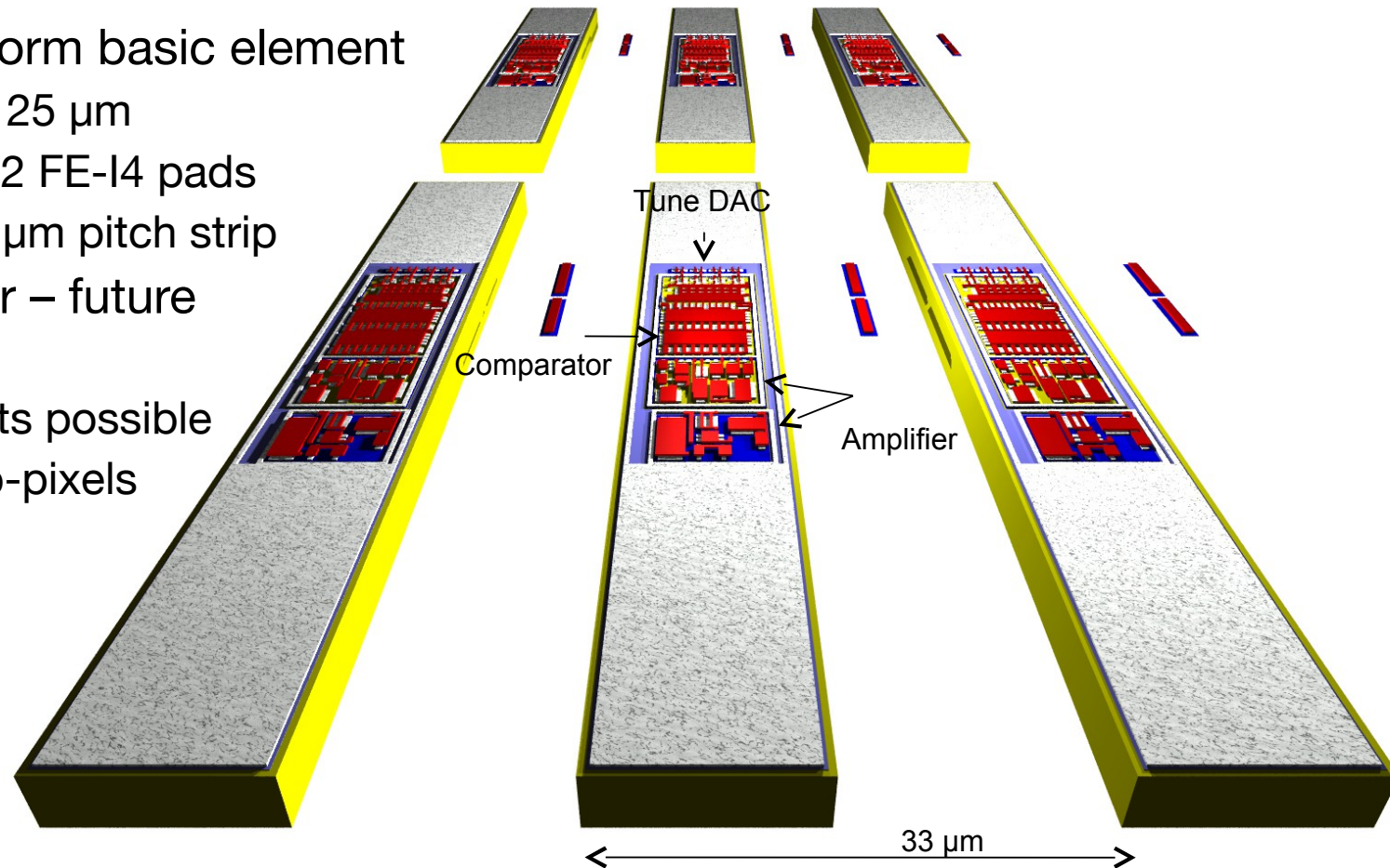
- University of Bonn
M. Backhaus, L. Gonella, T. Hemperek, F. Hügging, H. Krüger, T. Obermann, N. Wermes
- LBNL
M. Garcia-Sciveres
- CERN
M. Capeans, S. Feigl, M. Nessi, H. Pernegger, B. Ristic
- University of Geneva
S. Gonzalez-Sevilla, D. Ferrere, G. Iacobucci, D. La Marra, A. La Rosa, A. Miucci, D. Muenstermann
- University of Goettingen
M. George, J. Große-Knetter, A. Quadt, J. Rieger, J. Weingarten
- University of Glasgow
R. Bates, A. Blue, C. Buttar, D. Hynds
- University of Heidelberg
C. Kreidl, I. Peric
- CPPM
P. Breugnon, P. Pangaud, D. Fougeron, F. Bompard, J.C. Clemens, J. Liu, M. Barbero, A. Rozanov

HV2FEI4

- A combined active strip/pixel sensor was designed and produced
 - strips compatible with ATLAS ABCN and LHCb/Alibava Beetle
 - pixels match new ATLAS FE-I4 readout chip
 - capacitive coupling
 - bump-bonding possible

- Structure

- 6 sub-pixels form basic element
 - each $33 \times 125 \mu\text{m}$
 - connect to 2 FE-I4 pads
 - form a $100 \mu\text{m}$ pitch strip
- small fill factor – future options:
 - more circuits possible
 - smaller sub-pixels

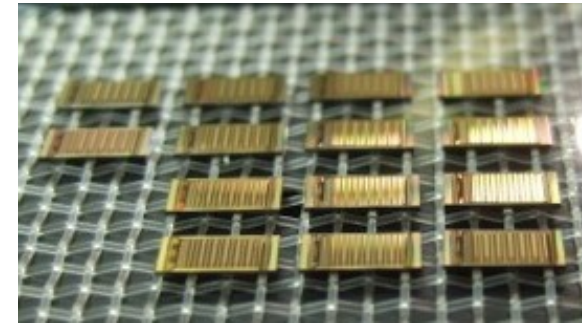


HV2FEI4 v1

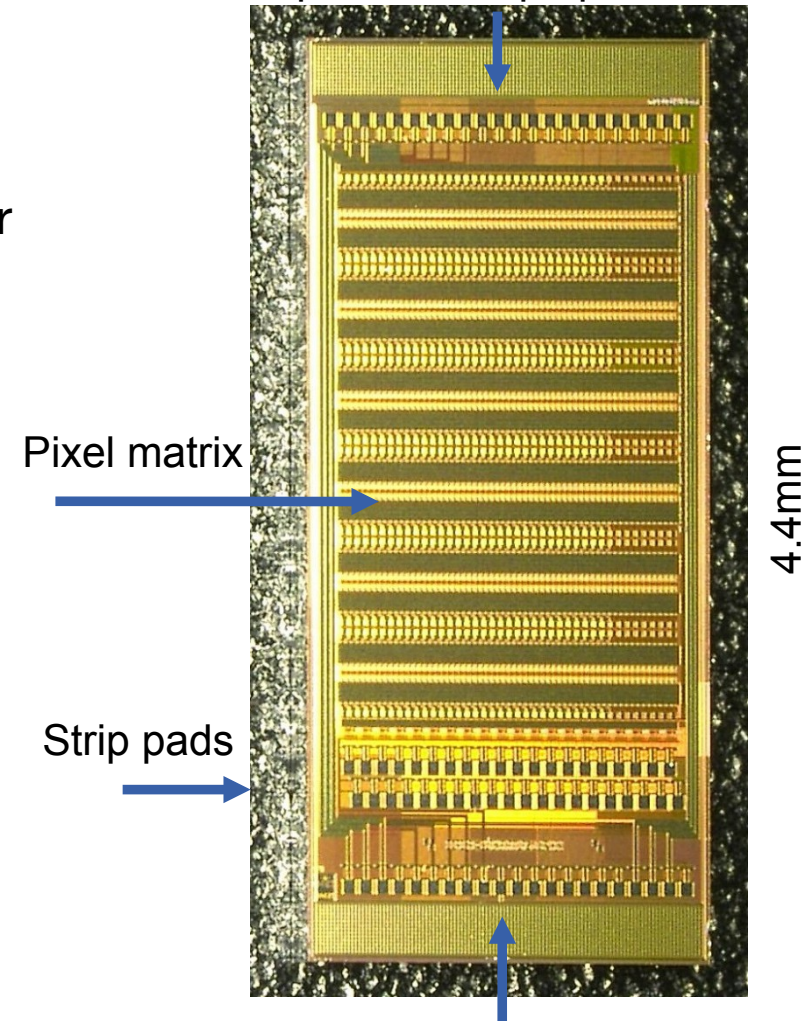
- Chip size: 2.2mm x 4.4mm
- Pixel matrix: 60x24 (sub-)pixels of 33 μm x 125 μm
- 21 IO pads at the lower side for CCPD operation
- 40 strip-readout pads (100 μm pitch) at the lower side and 22 IO pads at the upper side for (virtual) strip operation
- On chip bias DACs
- Pixels contain charge sensitive amplifier, comparator and tune DAC
- Configuration via FPGA or μC : 4 CMOS lines (1.8V)

3 possible operation modes

- standalone on test PCB
- strip-like operation
- pixel (FE-I4) readout



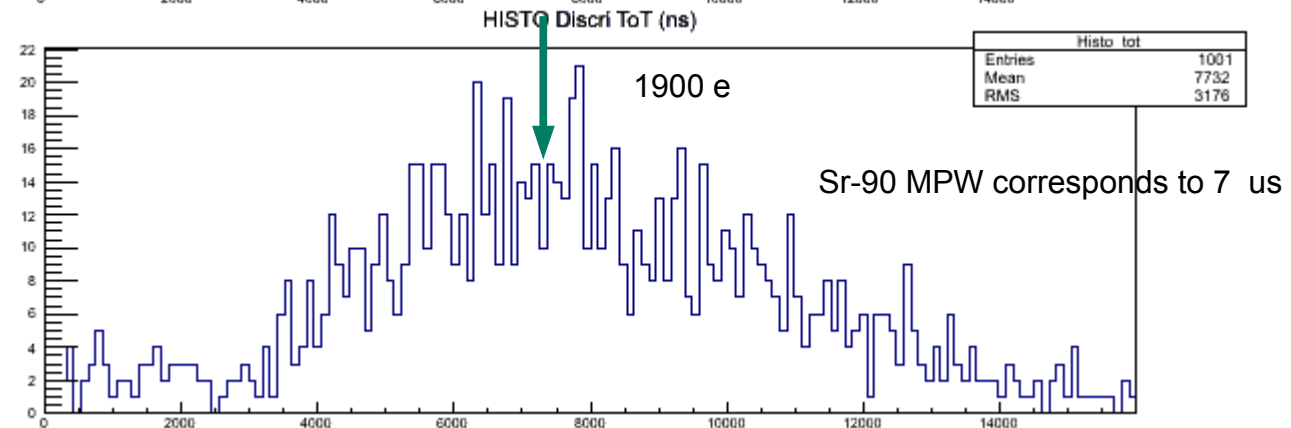
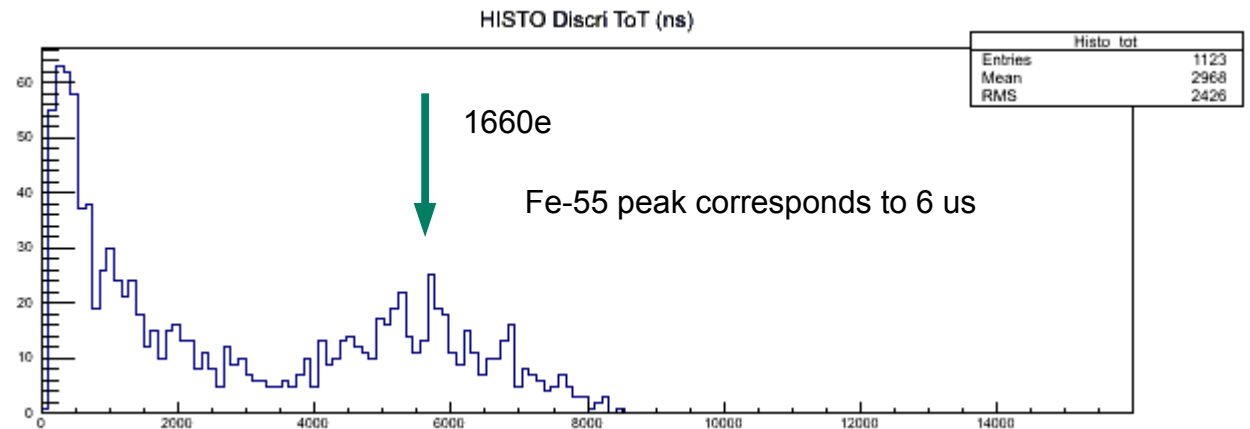
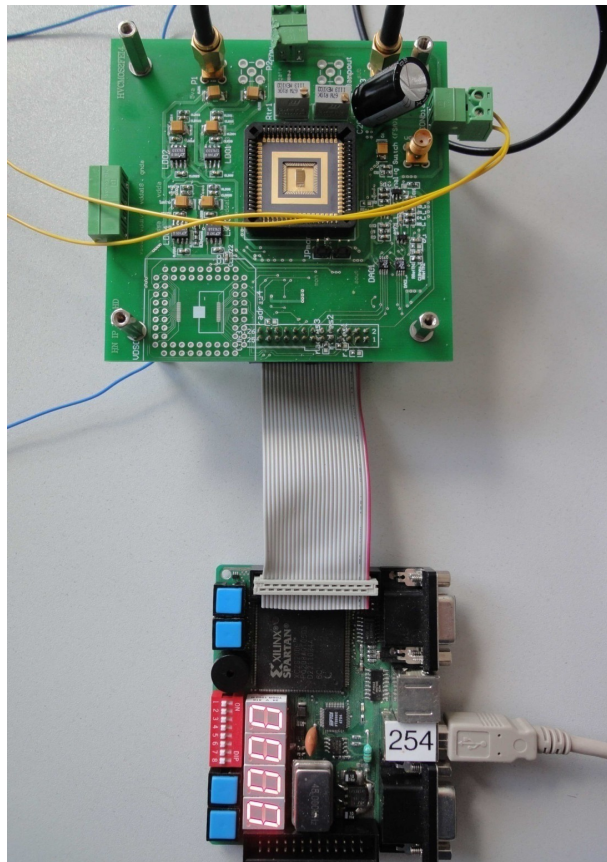
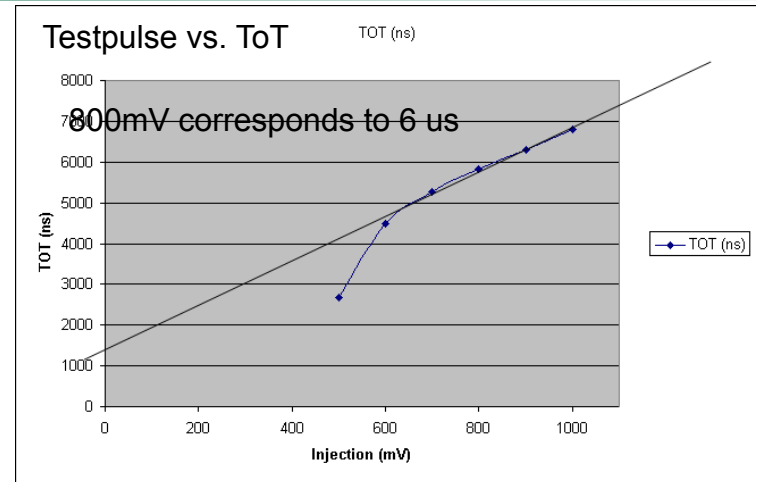
IO pads for strip operation



IO pads for CCPD operation

HV2FEI4: characterisation

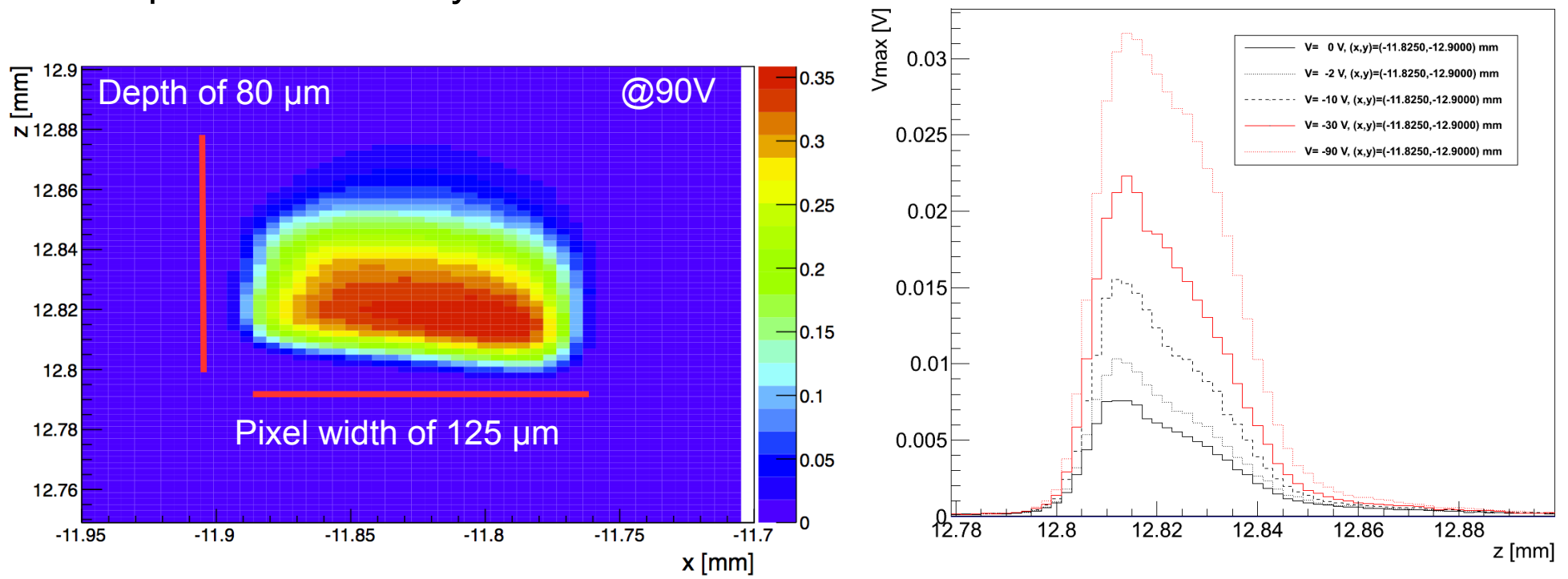
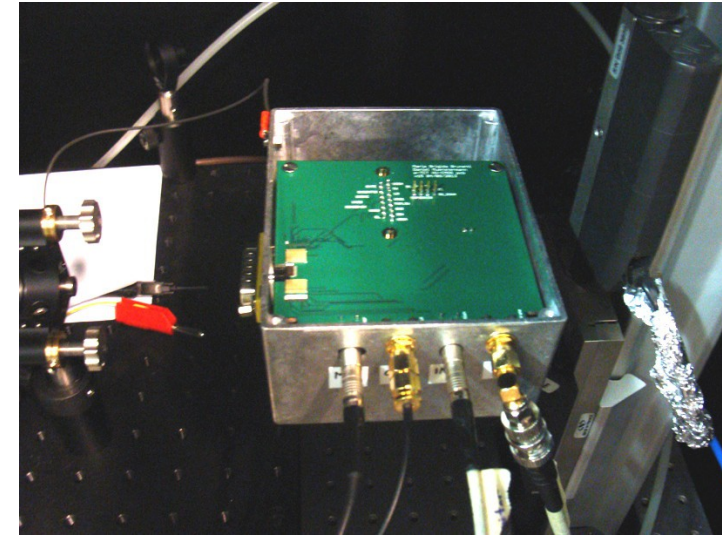
- standalone, using monitor output
- noise: $\sim 75 e^-$
- MPW for ^{90}Sr at 60V: $\sim 1900 e^-$
 - would mean more than $20\mu\text{m}$ active depth?
Diffusion? Unexpected field? \rightarrow eTCT
 - corresponds to 900mV injection



Sr-90 MPW corresponds to $\sim 900\text{mV}$ injection amplitude

eTCT

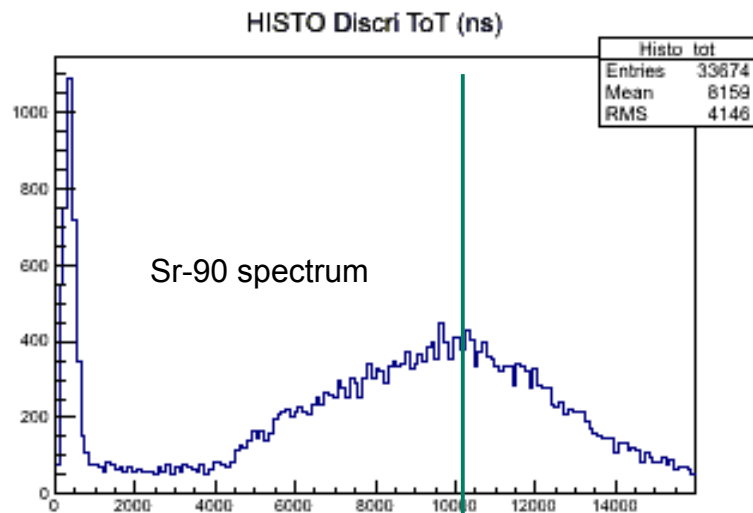
- performed in M. Moll's group at CERN with Marcos Fernandez Garcia and Maria Brunetti
- access only to preamplifier output
 - direct access to n-well in next submission
- sidewall not polished for 1st attempt
- first indications of unirradiated sample:
 - much deeper signal detection than assumed
 - HV has not much influence → mainly diffusion?
- samples on their way to JSI for irradiation



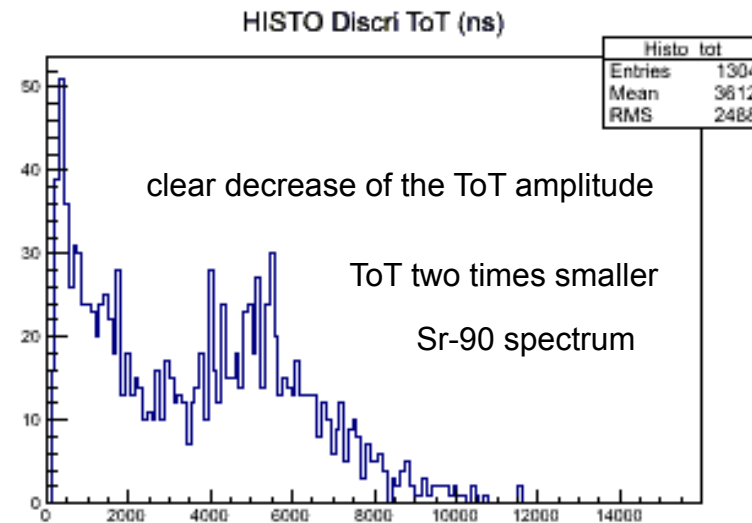
HV2FEI4: irradiation

- First irradiations conducted at CERN/PS and with an x-ray tube
 - on special PCB allowing for remote operation, HV2FEI4 powered and read-out during irradiation

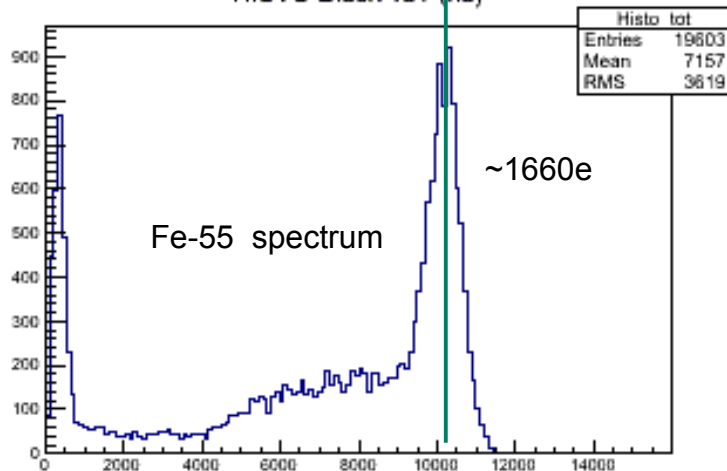
un-irradiated device



CCPD9 irradiated at 80 MRad

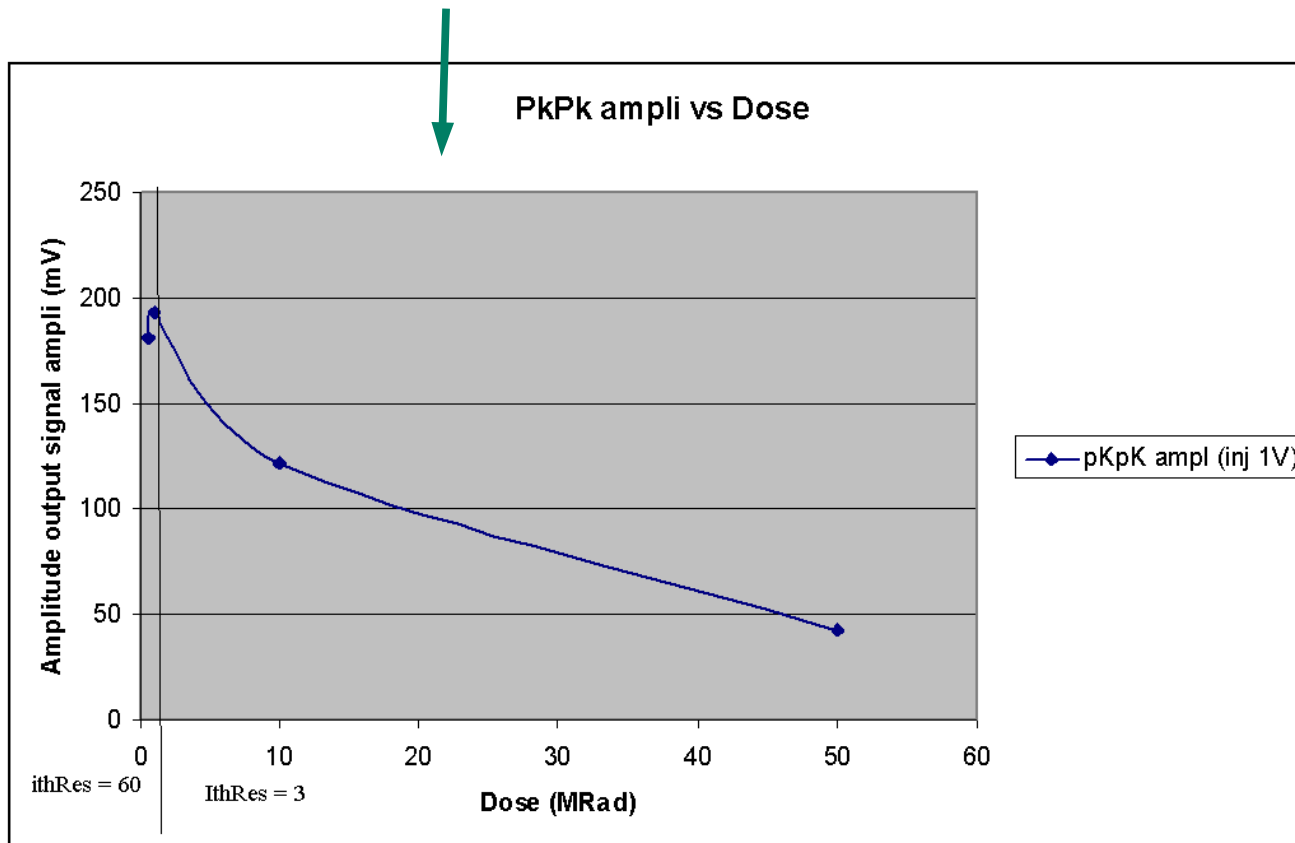


HISTO Discr ToT (ns)



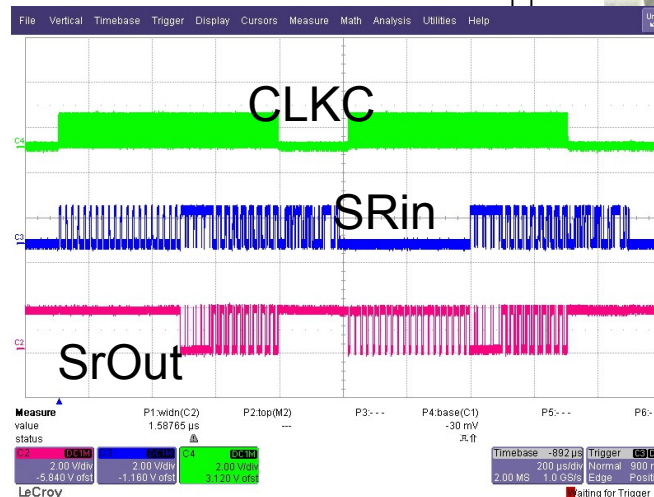
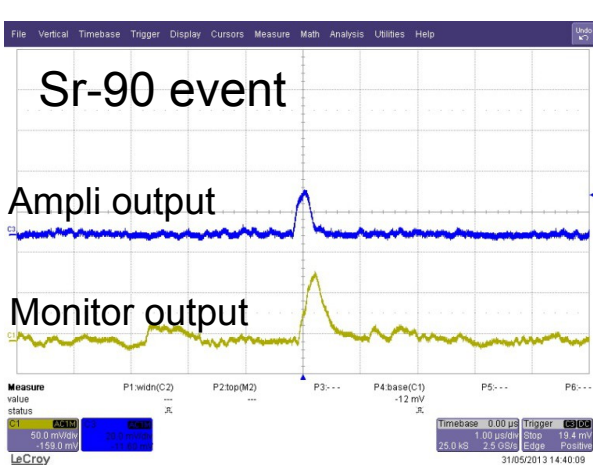
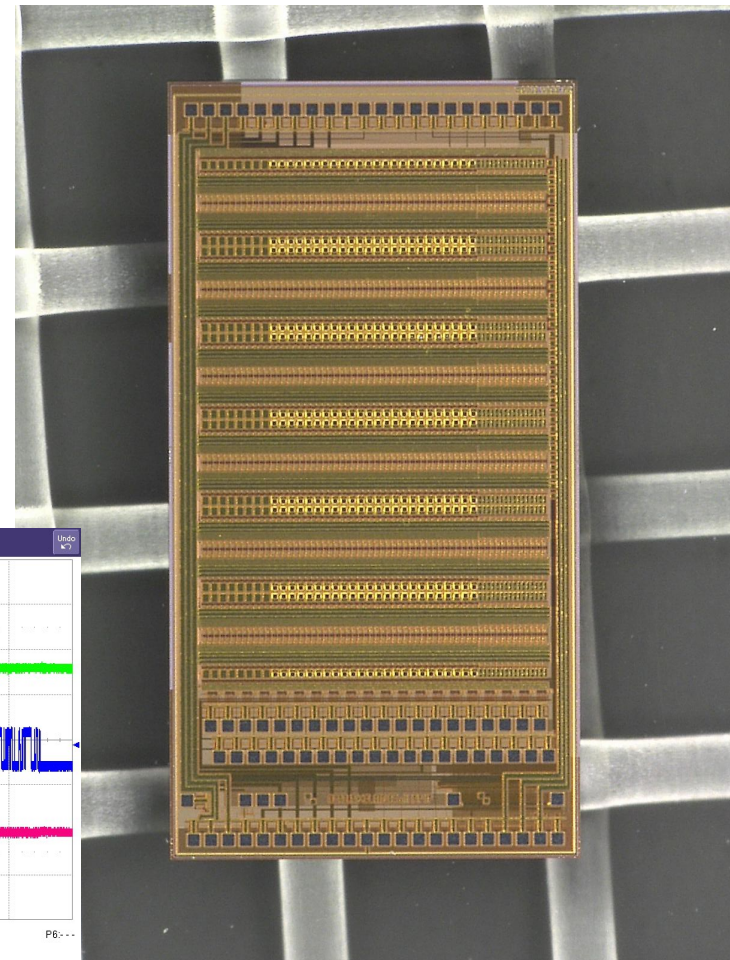
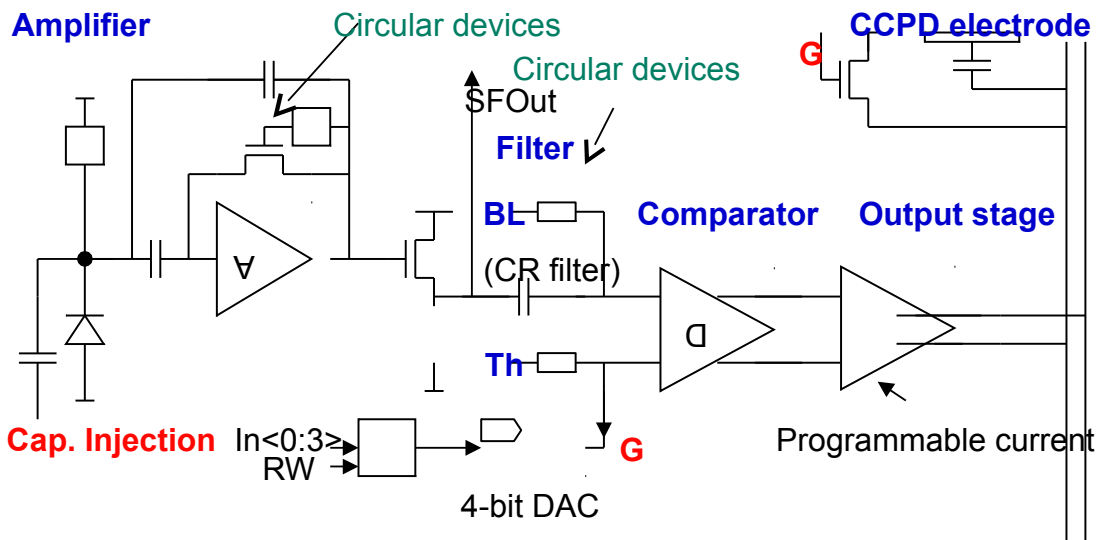
HV2FEI4: irradiation

- First irradiations conducted at CERN/PS and with an x-ray tube
 - on special PCB allowing for remote operation, HV2FEI4 powered and read-out during irradiation
- clear radiation effects seen after proton and x-ray irradiation
 - drop in amplitude/amplification
 - also seen with test pulser input → electronics effect, rad-soft design



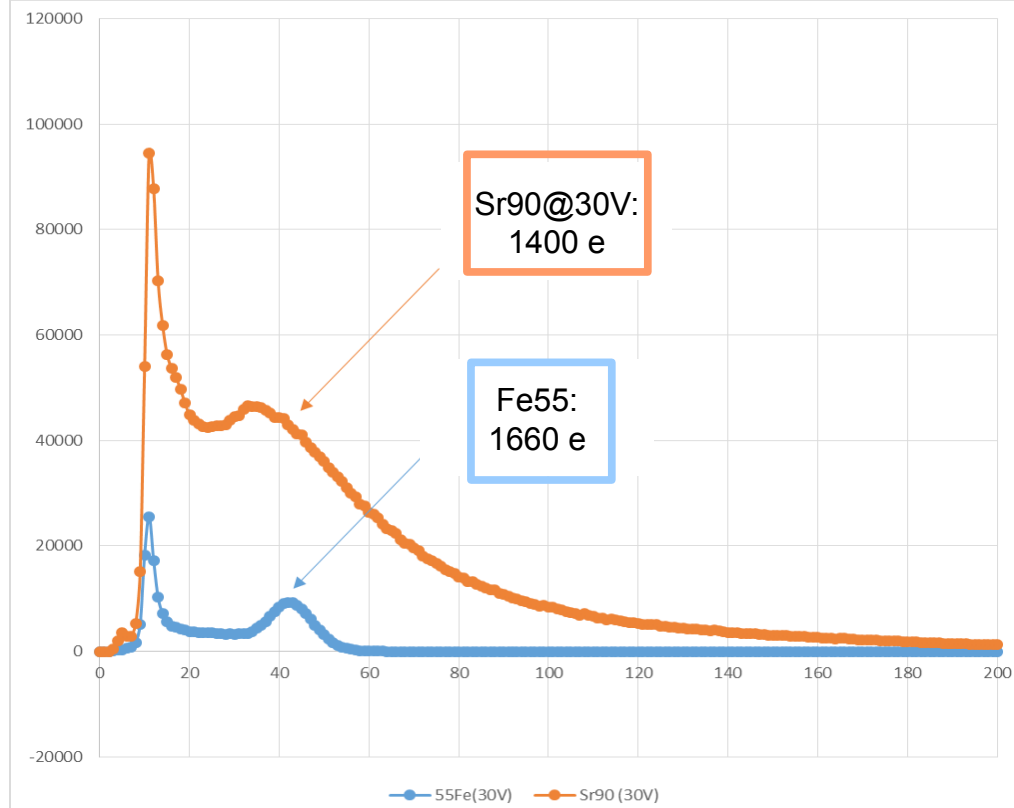
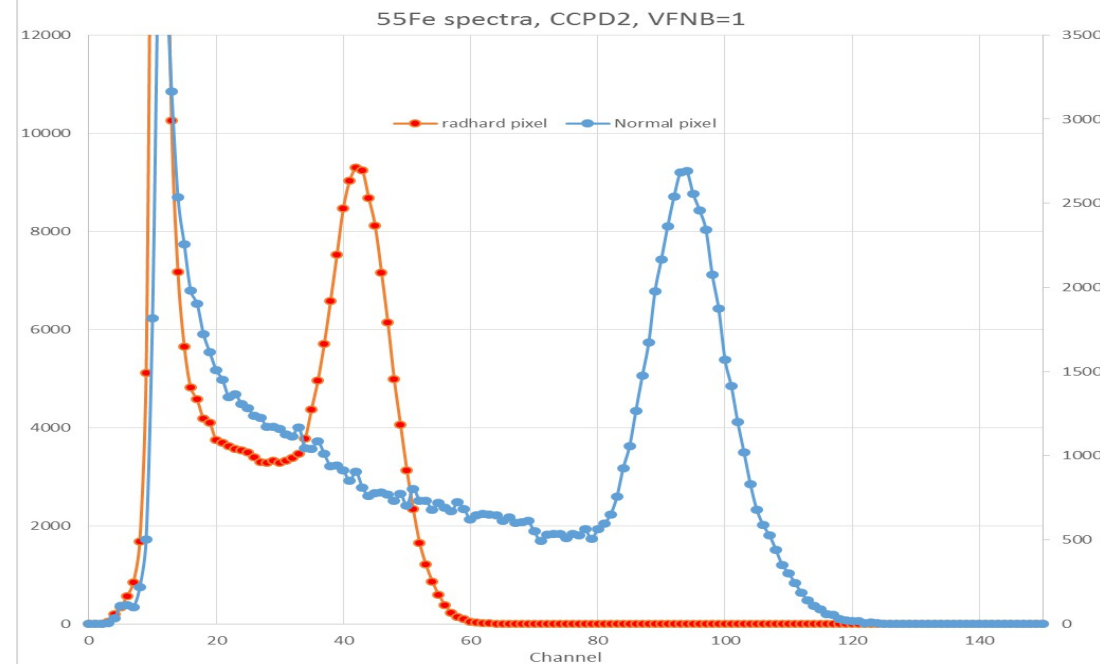
Rad-hardness: consequences

- deliberately chose “standard” design to see how far it would get
 - not far enough... → “harden” design by guard rings, circular transistors, ...
- HV2FEI4_v2 was submitted in November and received in April



HV2FEI4_v2

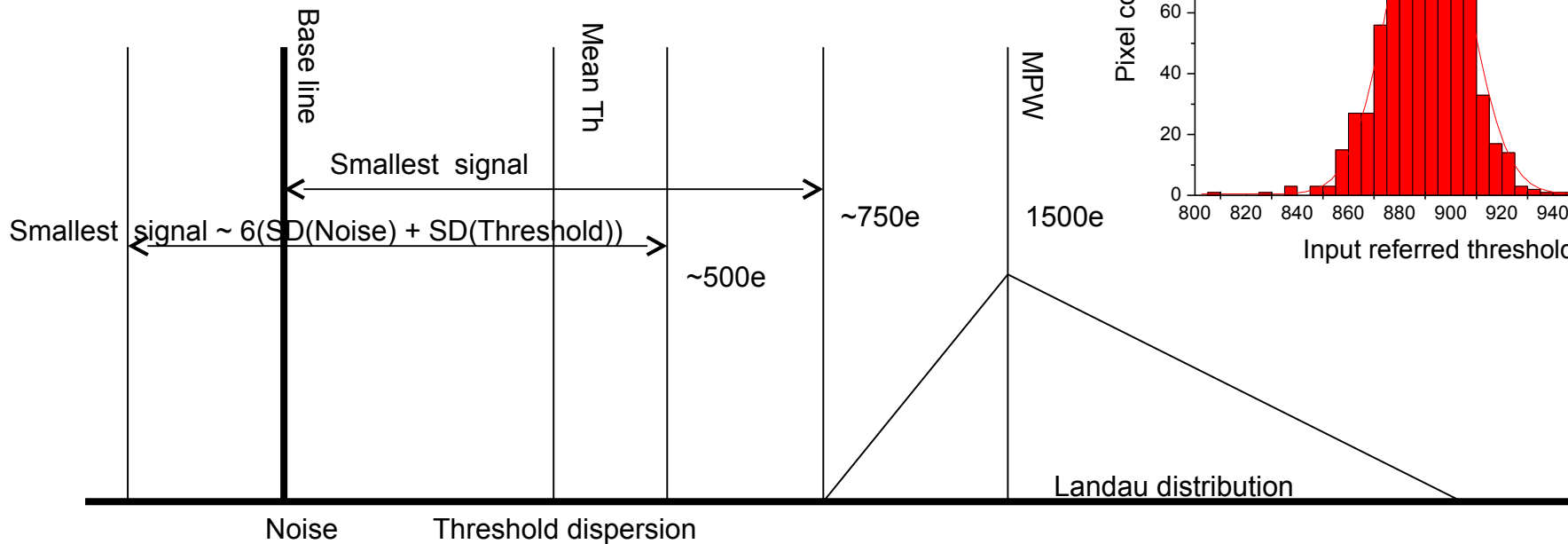
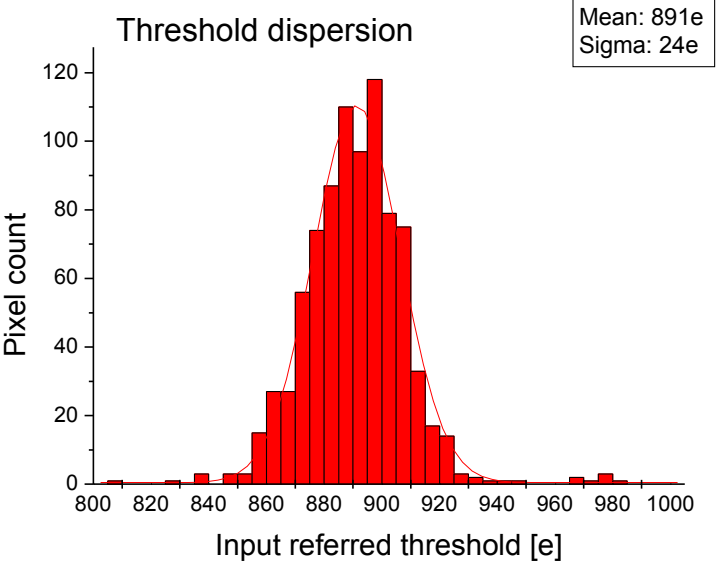
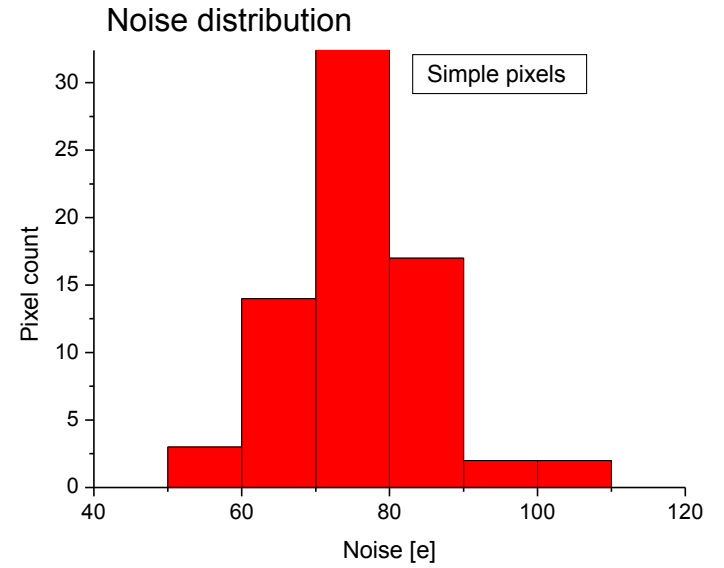
- Circuits generally optimised for rad-hardness, but 2 different designs tested:
 - “normal pixels”: mainly added guard rings around transistors
 - “rad-hard pixels”: all relevant transistors circular
 - more capacitance, lower gain at identical settings
- More measurements:
 - Sr-90 at 30V now at ~1400e





HV2FEI4_v2

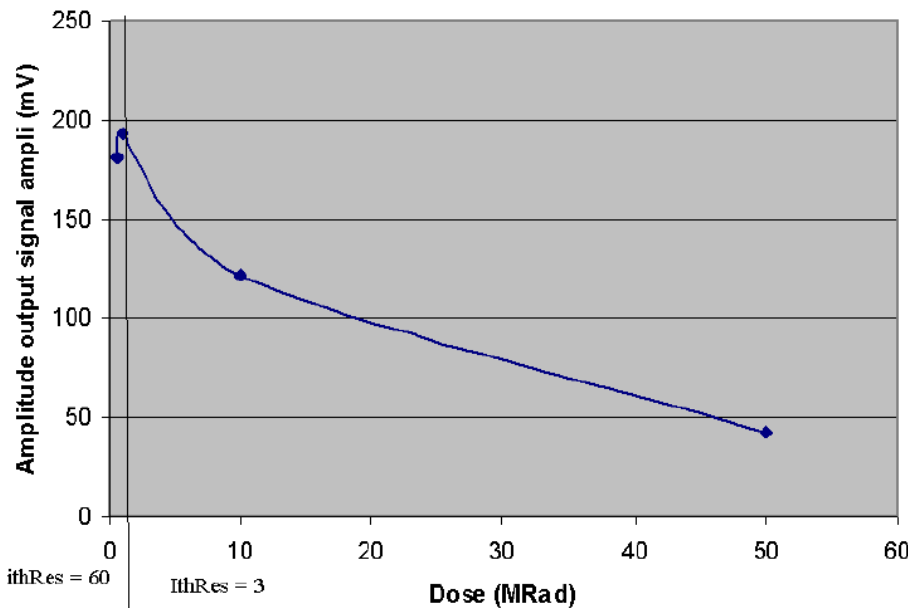
- Noise inferred from threshold scan, now around $75e^-$
- Threshold tuning implemented, threshold dispersion $\sim 25e^-$
- Fundamentally, the threshold is required to be lower than low energy end of the MIP landau
 - usually MPW/2 is specified
 - looks promising, but still work to do



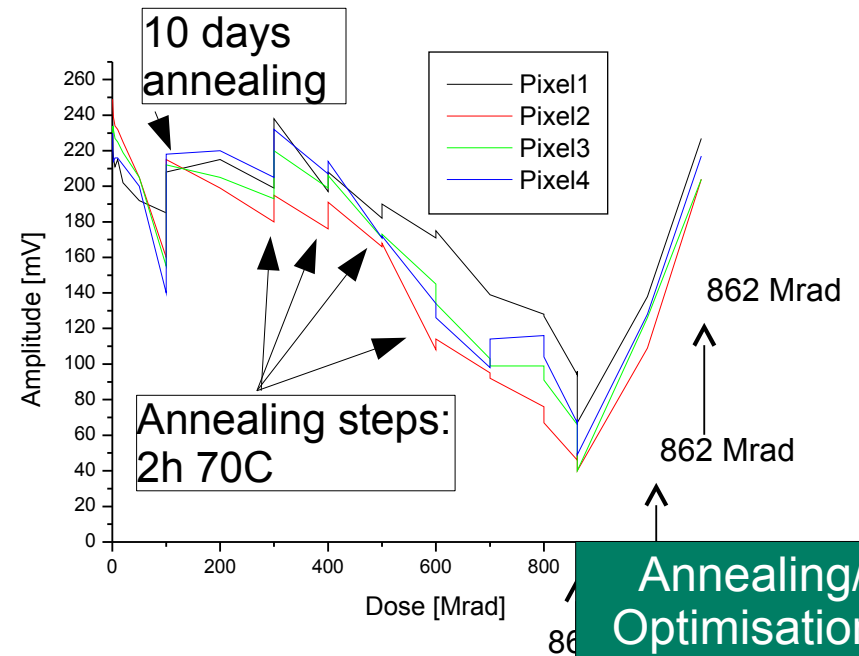
HV2FEI4_v2: rad-hardness

- Radiation effects due to dose, could be reproduced by x-ray irradiation
 - CERN PS currently down, but x-ray tube available
 - very fast irradiation, requires annealing to be mimic realistic dose rate
- Signal amplitude clearly much more stable
 - irradiated up to 862 Mrad (!), drop visible after ~500 MRad
 - dose rate effect, annealing brings signal back to ~100%

➔ rad-hardness significantly improved, hadron irradiations to follow



CCPD1 irradiated with x-rays
Amplifier gain loss

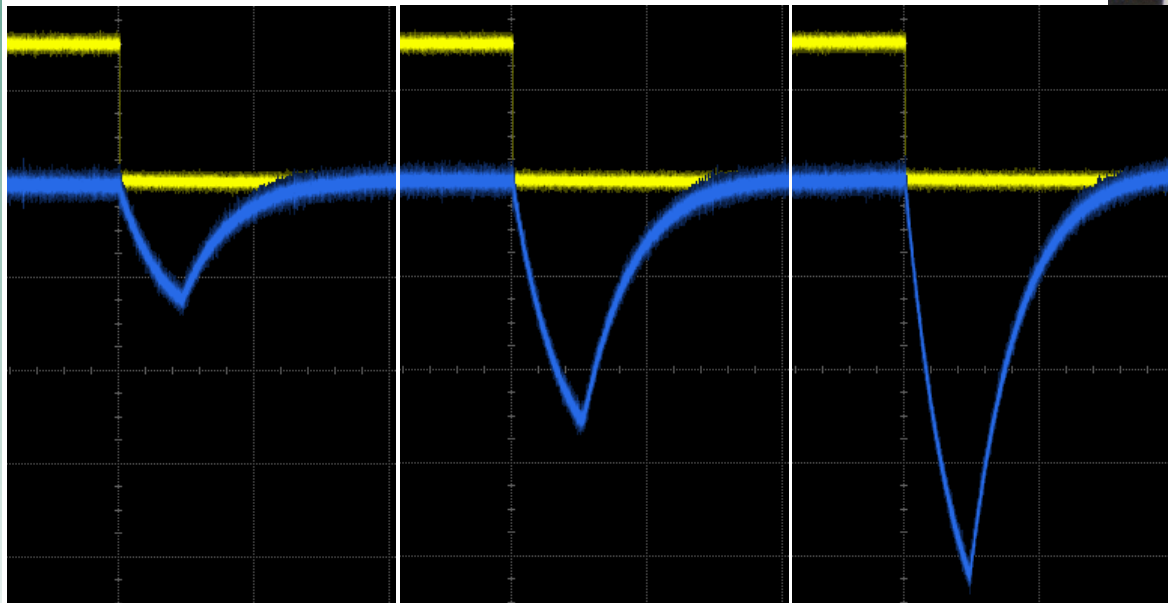


CCPD2 irradiated with x-rays
Amplifier gain loss
Rad hard pixels

Annealing/
Optimisation
of settings

HV2FEI4: strip readout

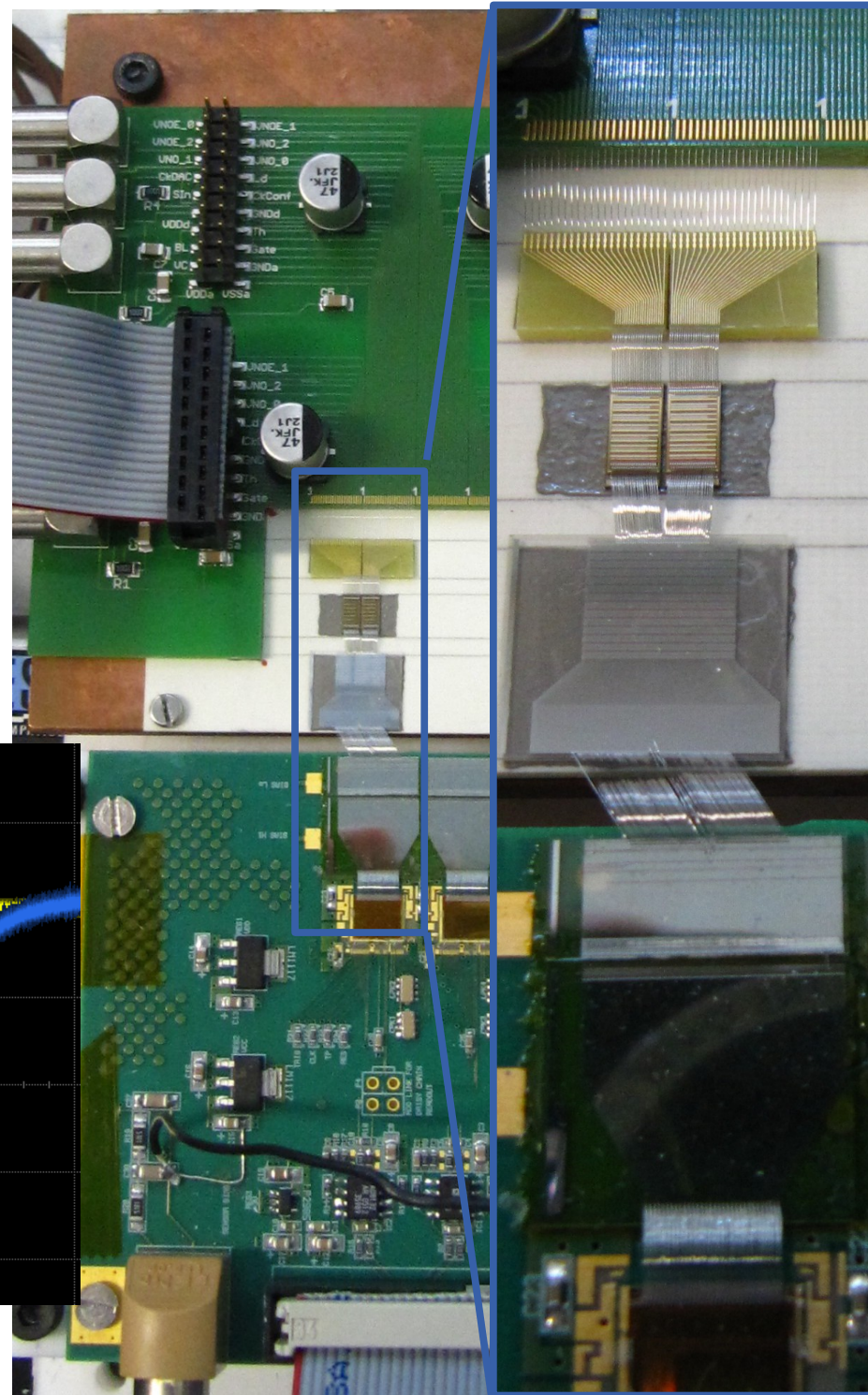
- Beetle/Alibava readout had issues with noise/common mode pickup
- configuration worked, “strips” could be switched on/off
- however, position-encoding works:
 - monitor output on scope
 - same principle on strip readout pads
- Supply PCB design changed
 - threshold now at reasonable values



Row 0

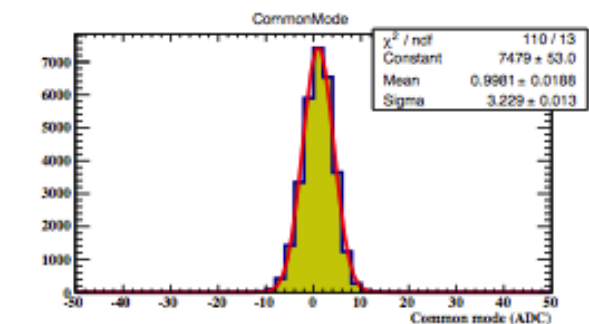
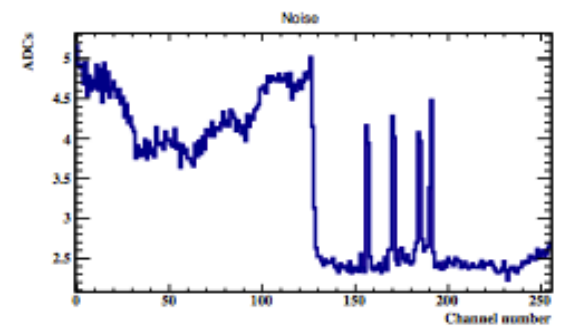
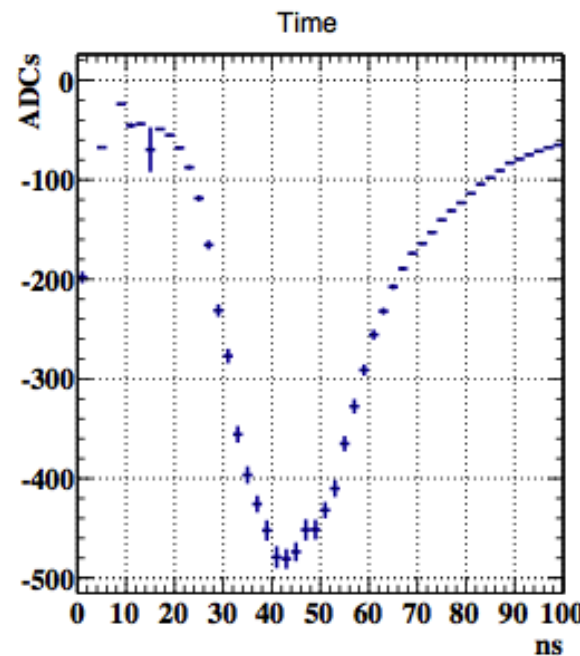
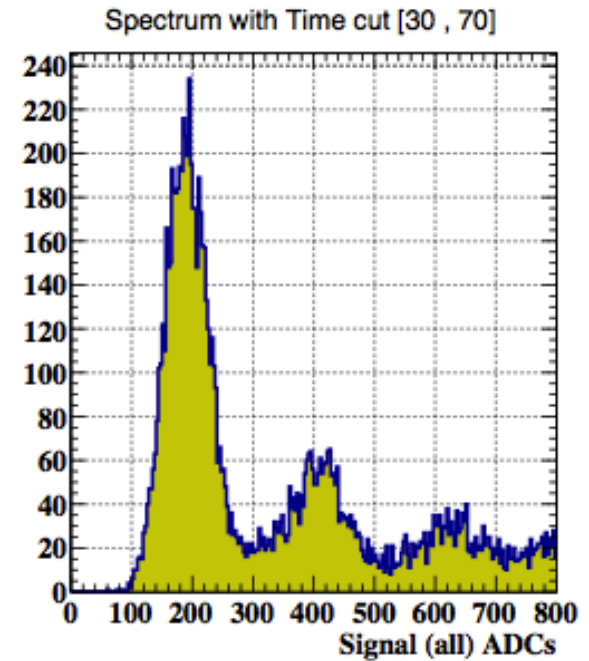
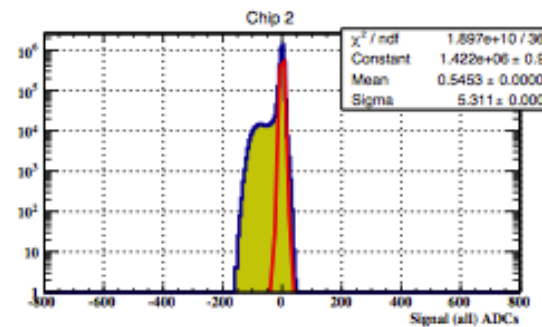
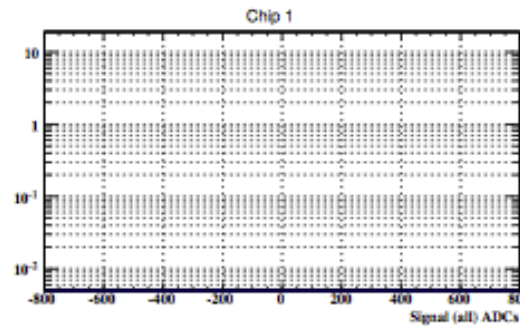
Row 12

Row 23



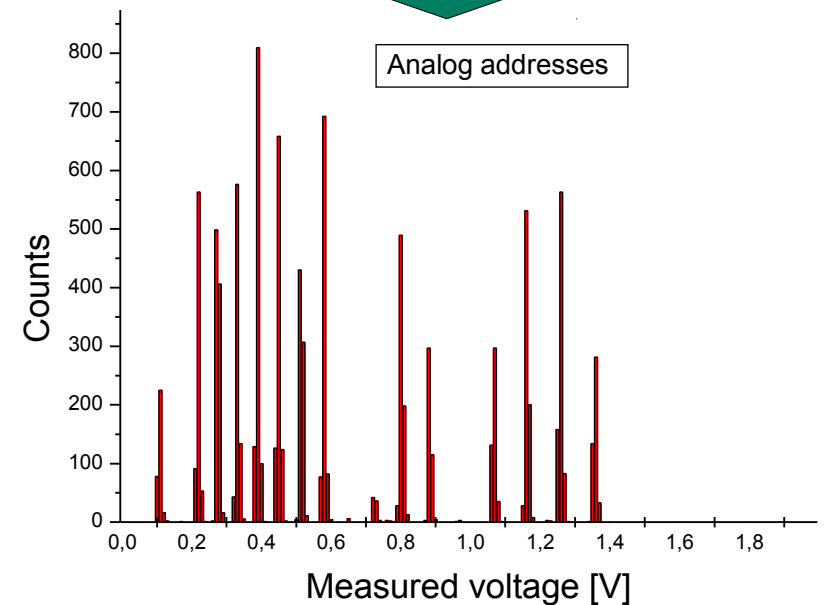
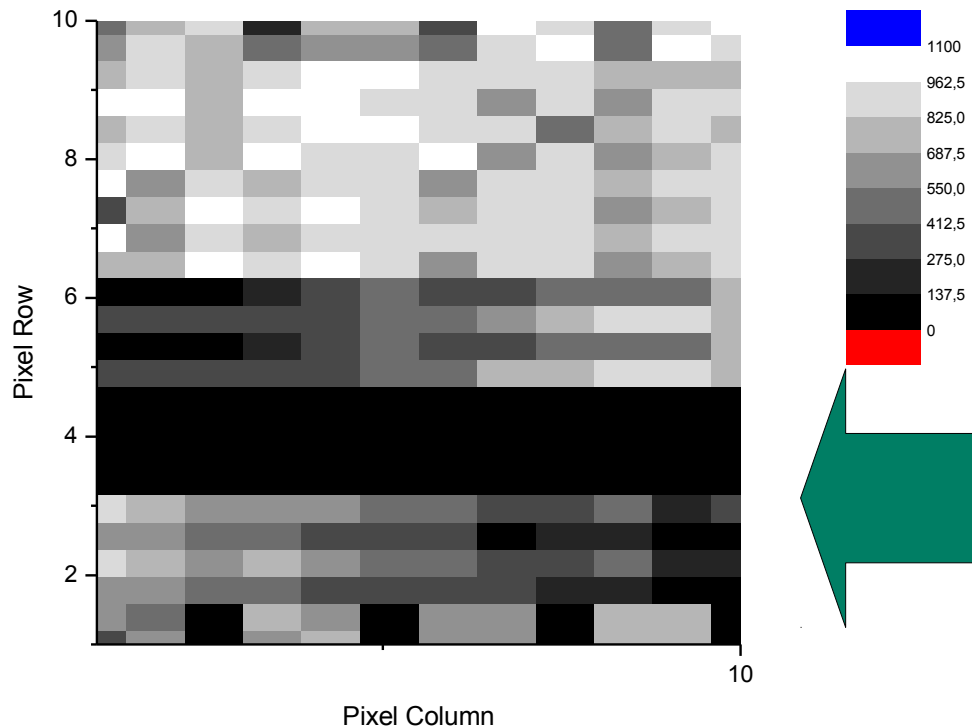
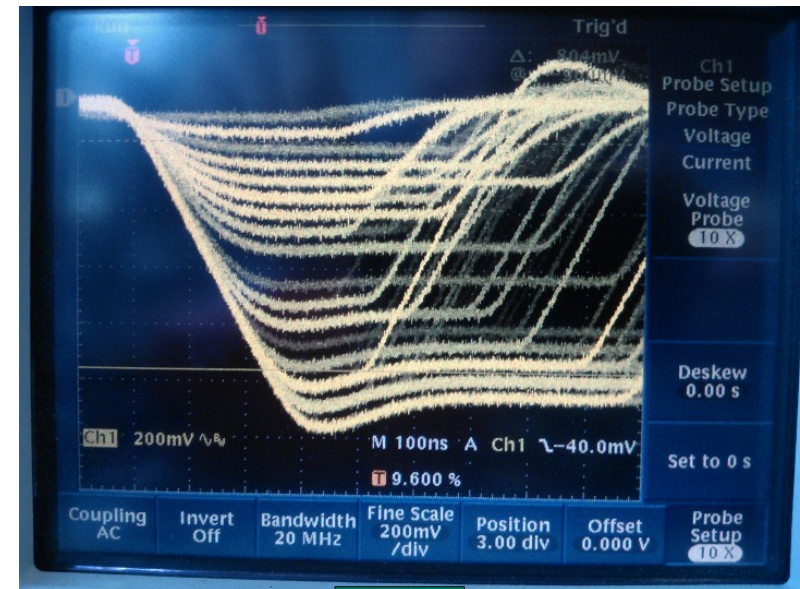
HV2FEI4: strip readout

- First results with Alibava readout
- Signals too large \rightarrow strange effects
- Working on offline-analysis taking into account all HVMCOS specifics



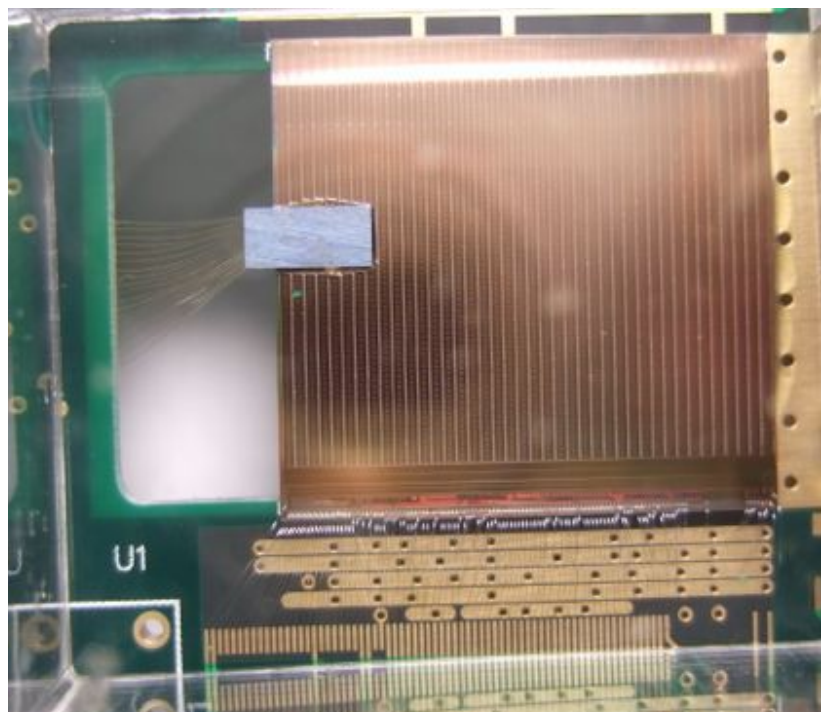
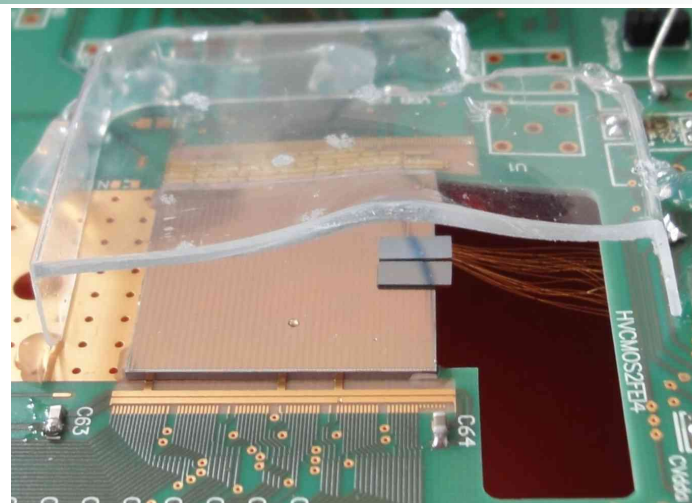
HV2FEI4_v2: strip performance

- First measurements again using an oscilloscope
- Fe-55 source illuminating a wire
 - shadow ~visible in pulse heights
 - can be decoded to give a pixel hitmap using only strip information



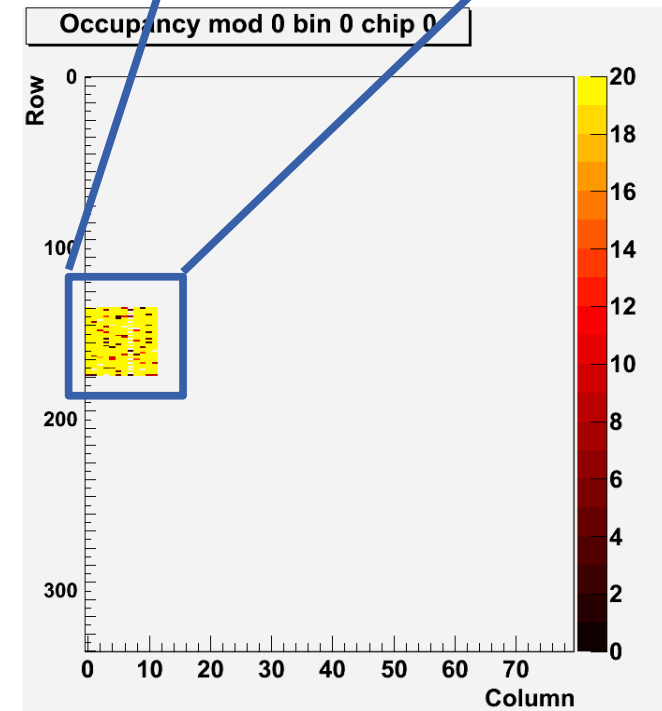
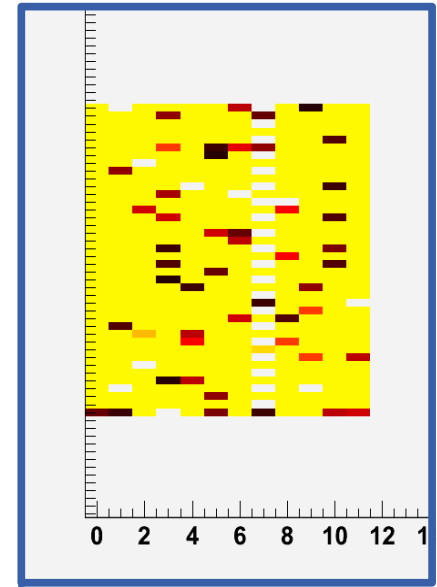
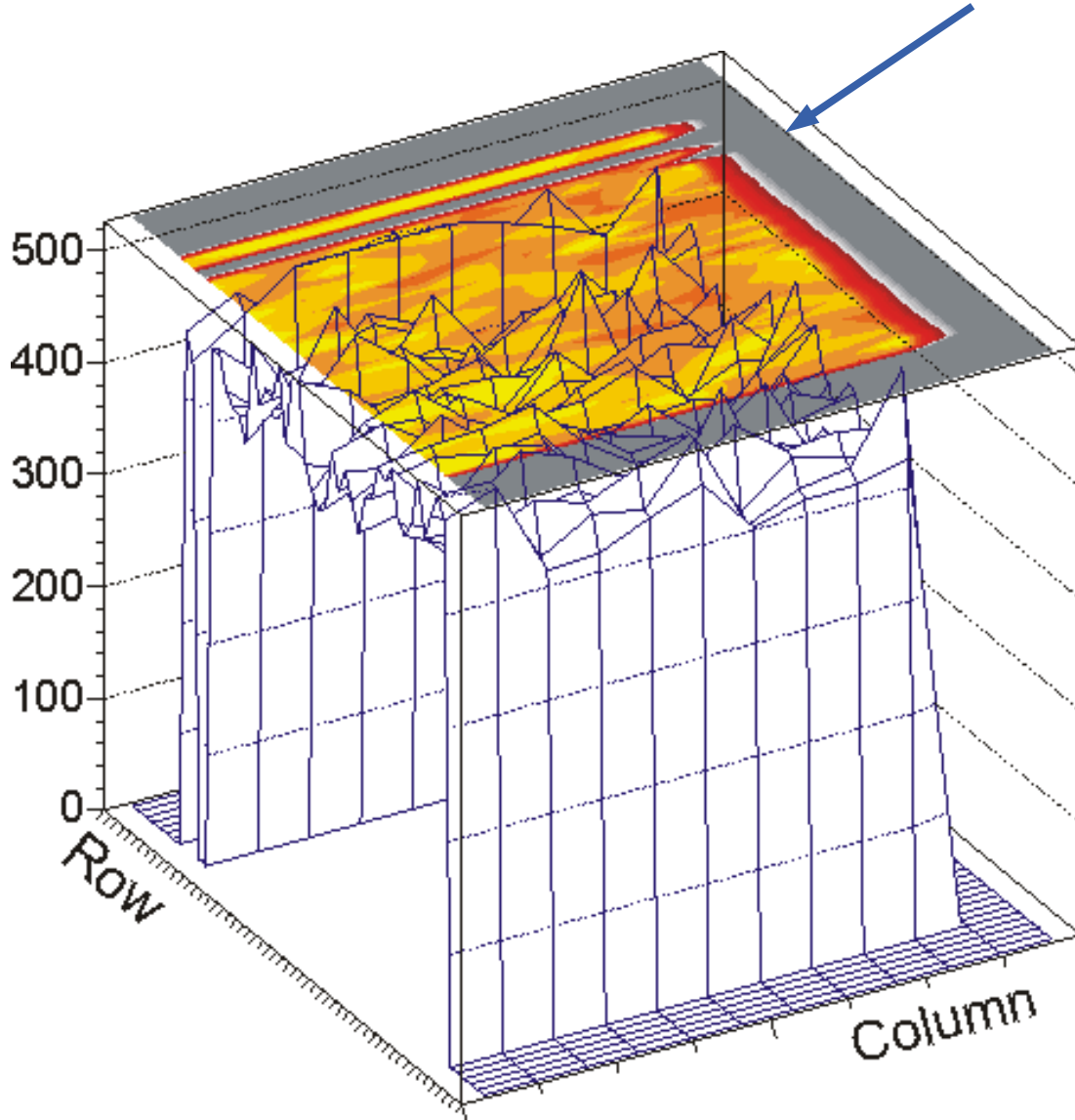
HV2FEI4: Pixel readout

- Several HV2FEI4s glued to FE-I4A and FE-I4B
- HV2FEI4 wirebonds done through hole in PCB
 - could be bumps or TSVs later



HV2FEI4: Pixel readout

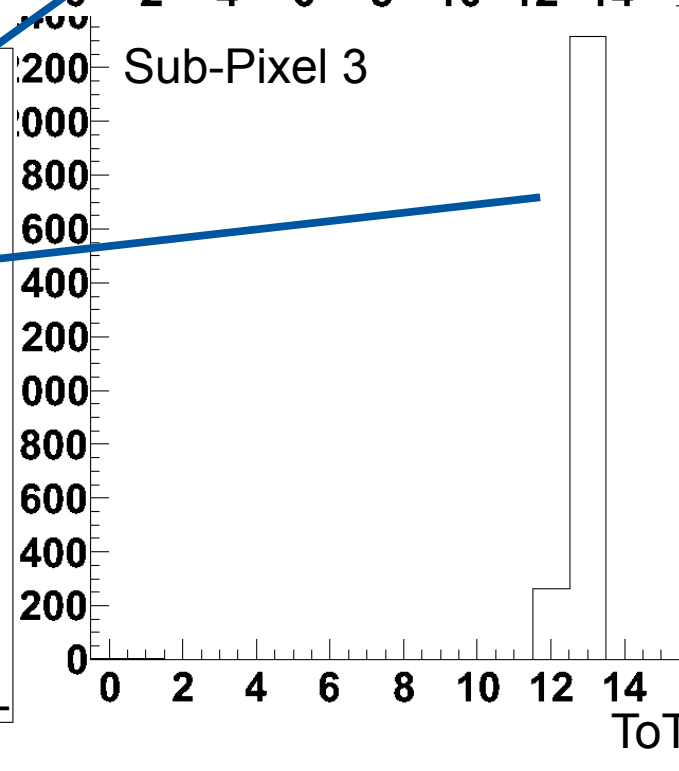
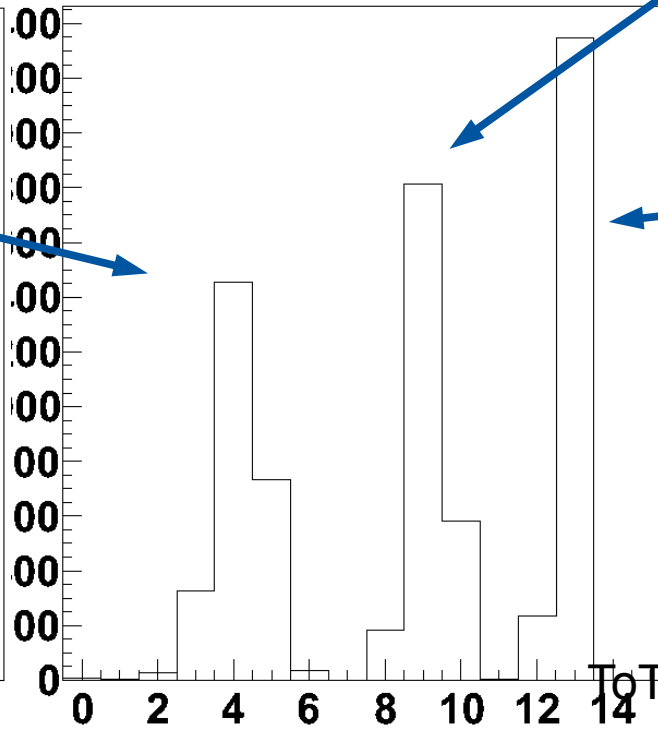
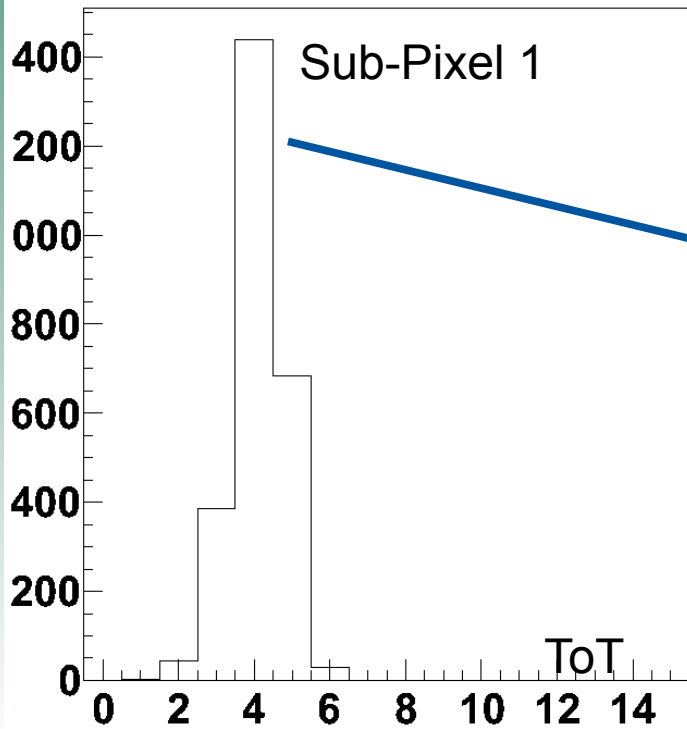
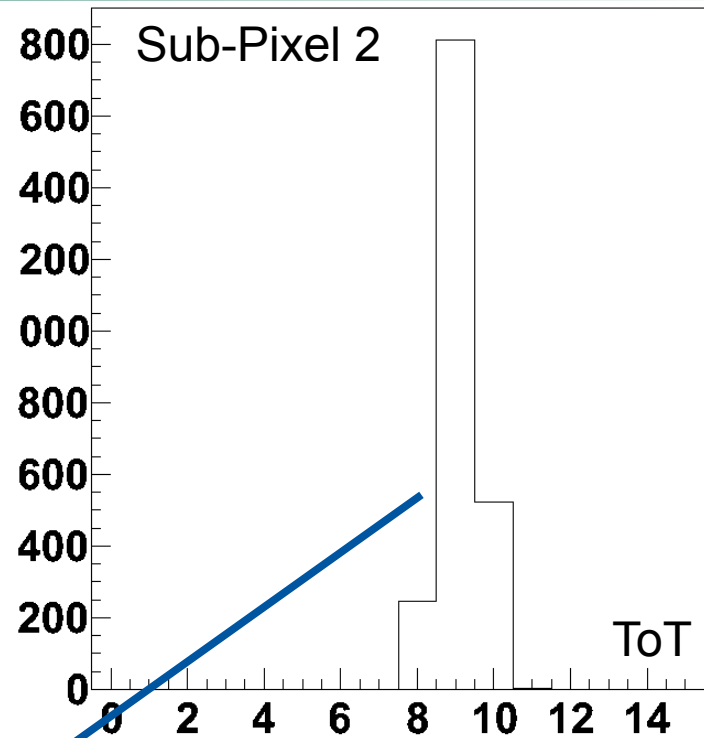
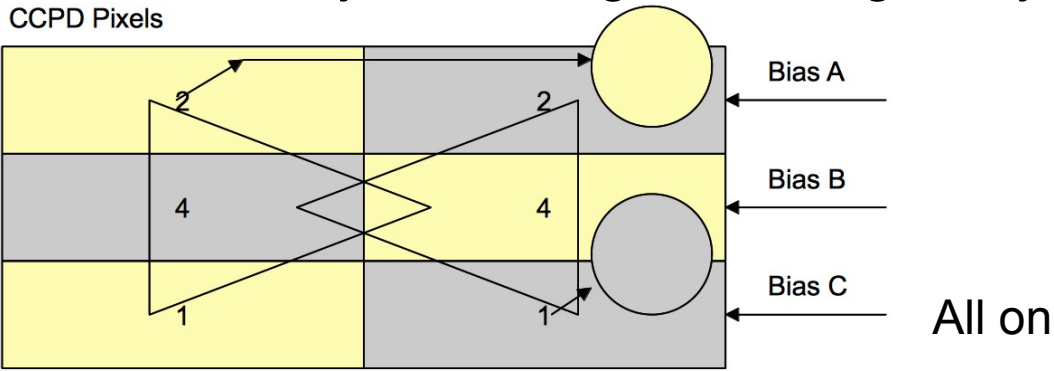
- First measurements:
 - FE-I4A (w/ bumps) sees HV2FEI4 being glued to it
 - Physics (^{22}Na source) is seen by FE-I4B (w/o bumps)





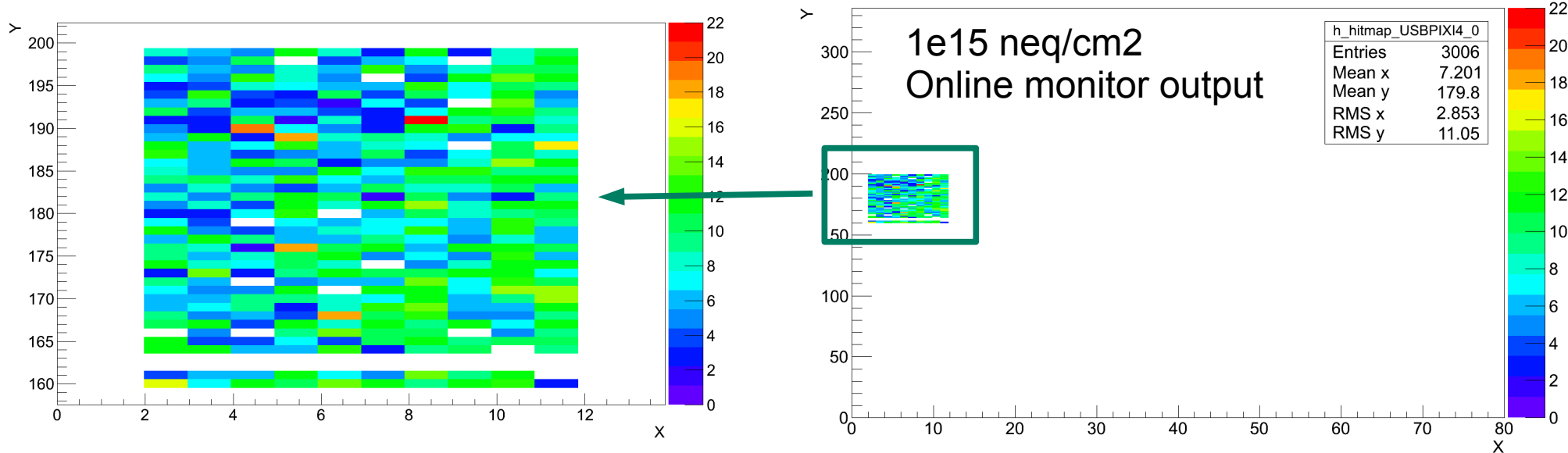
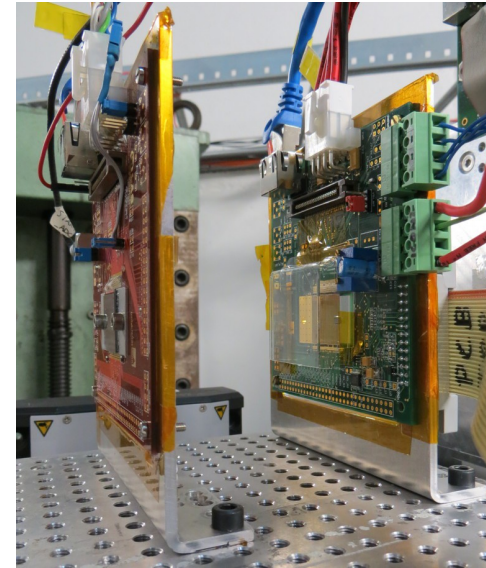
HV2FEI4: Pixel readout

- ToT encoding:
 - 3 sub-pixels clearly distinguishable
→ sub-pixel encoding works!
 - to do: dynamic range matching, array tuning



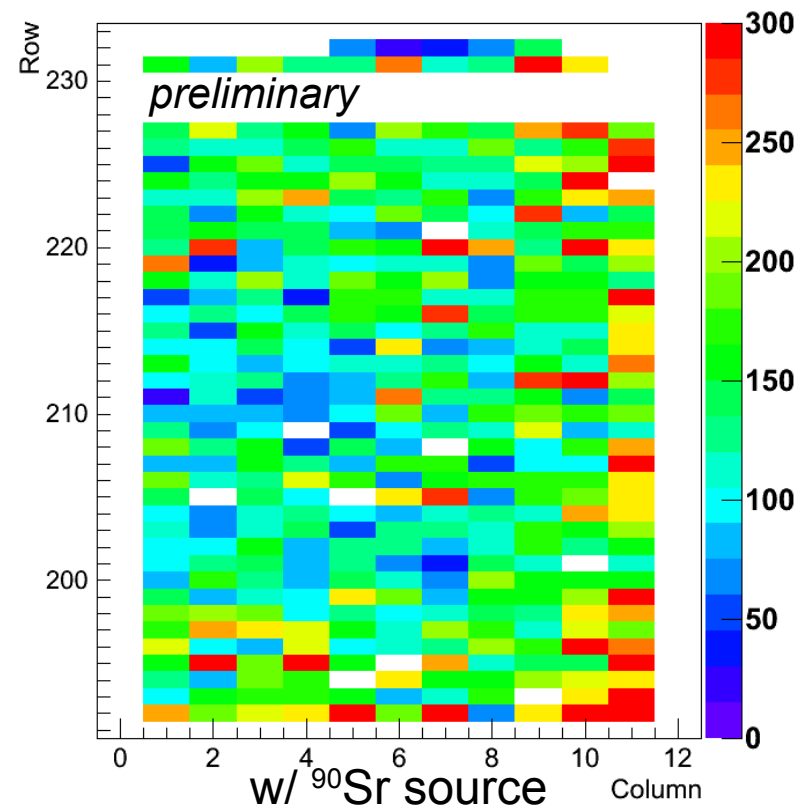
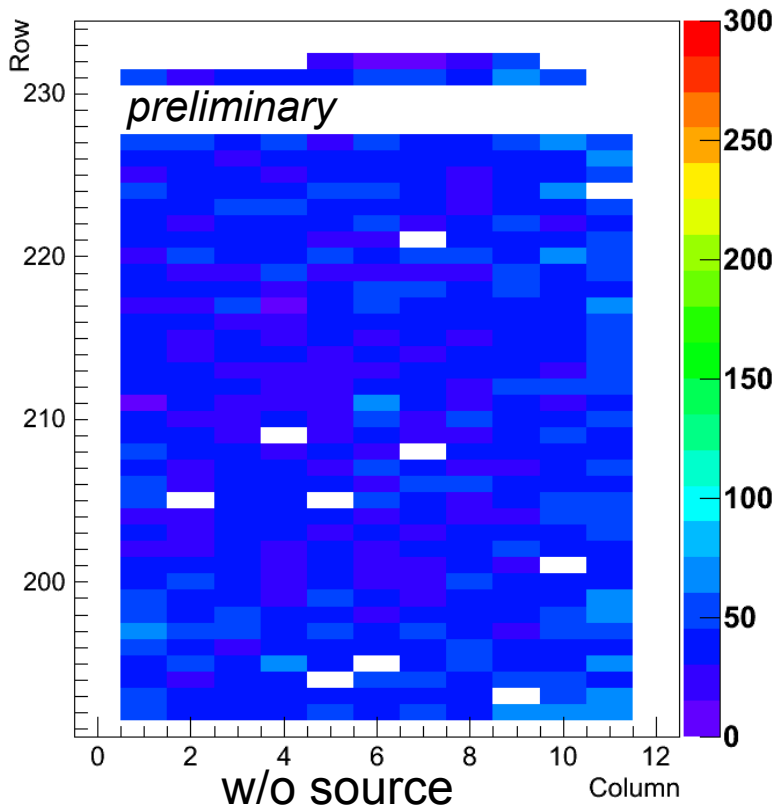
HV2FEI4: Pixel readout in testbeam

- First data taken at DESY testbeam in August
 - unirradiated and reactor neutron (JSI) irradiated devices: $1e15$, $1e16$ neq/cm²
- Issues with DUT data stream merging, reconstruction efforts still ongoing
- Nevertheless, clear evidence
 - HV-CMOS also works in “hostile” testbeam environment
 - unirradiated and $1e15$ neq/cm² sample yield similar rates (even w/o cooling!)
 - indication(!) for reasonable efficiency at 60V and after full strip fluence
 - noise still around $\sim 80e^-$
 - $1e16$ sample sees increased, but low rate with beam



n-irradiated behaviour: $1e16$ n_{eq}/cm^2

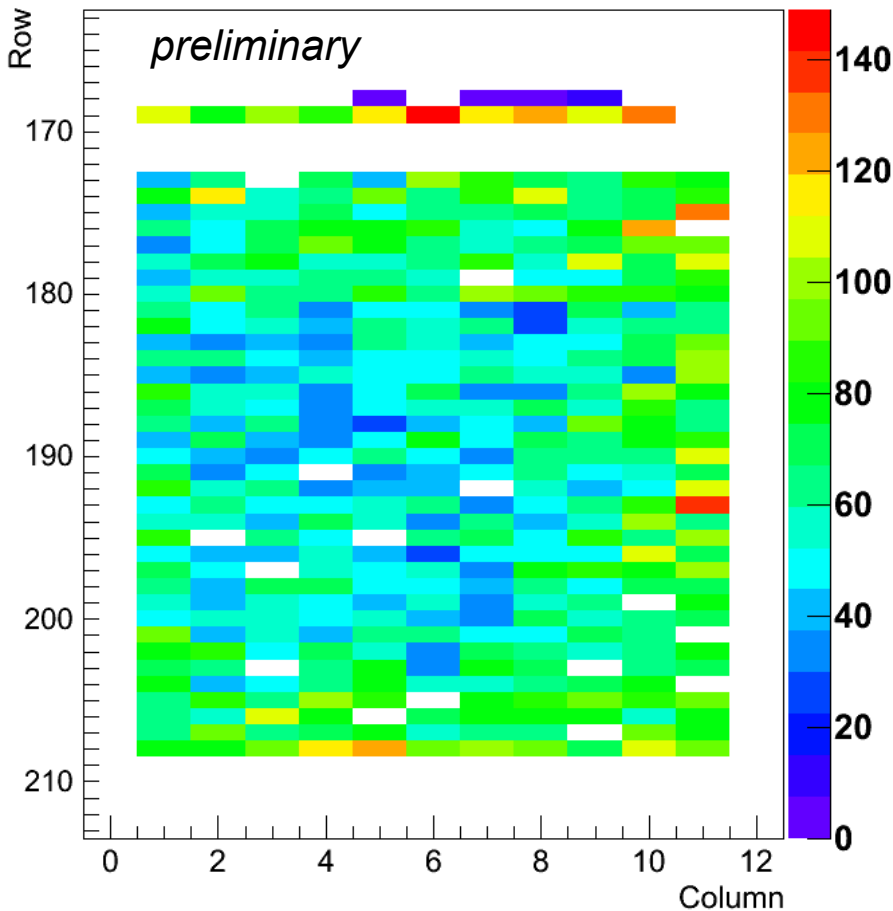
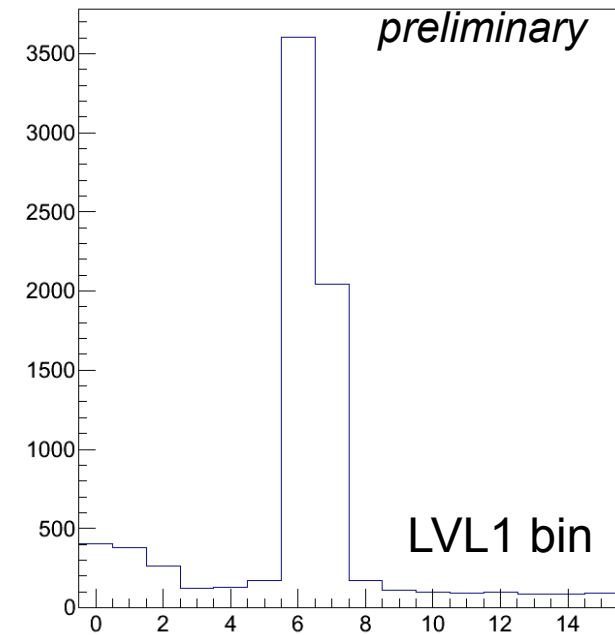
- irradiation done at JSI Ljubljana w/o biasing, low TID
- up to now measurements at room temperature (!)
- following measurements with (only) -20V to -25V bias voltage
- noise at RT ~ 280 e^- \rightarrow rather high threshold (uncalibrated) necessary to obtain a noise occupancy of $\sim 10^{-10}$
- below: about ~ 10 minutes exposure, self-trigger (!) source scan with and without ^{90}Sr source



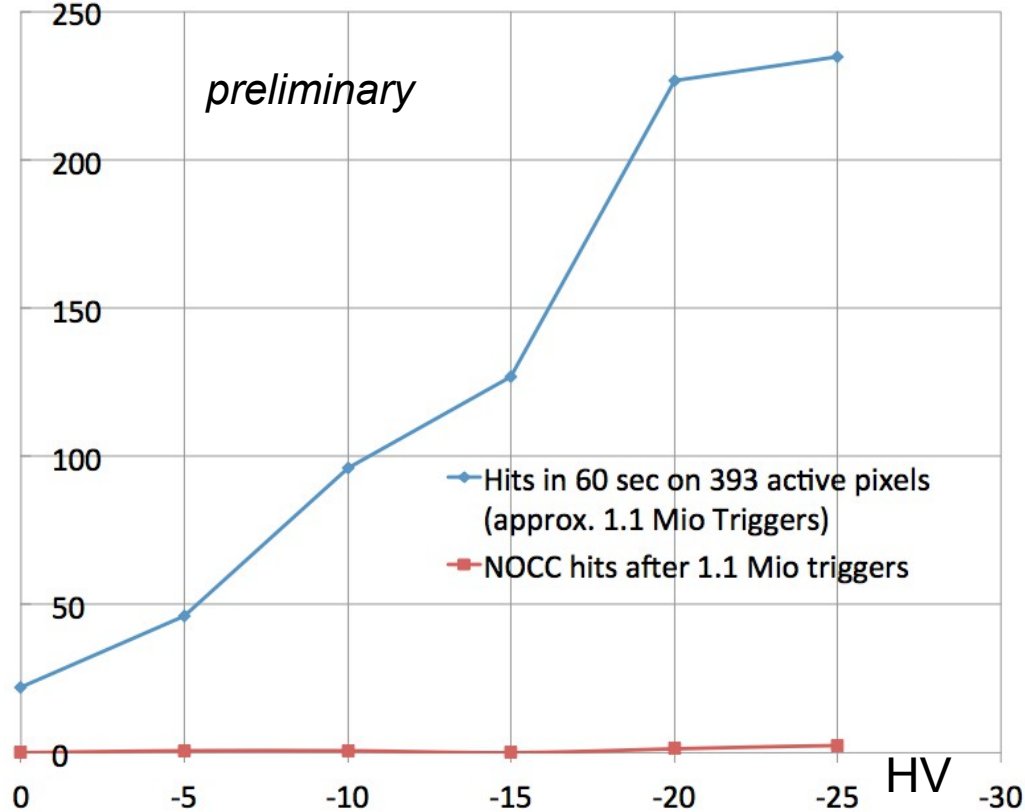


Irradiated behaviour: $1e16 \text{ n}_{\text{eq}}/\text{cm}^2$

- measurements with scintillator trigger
 - makes sure we select MIP-like electrons
 - avoids “noise” triggers
 - rate rises with HV as expected, but (rate) saturation not yet seen \rightarrow go higher in HV, cool
- next steps: calibration, cooled operation



Events/minute





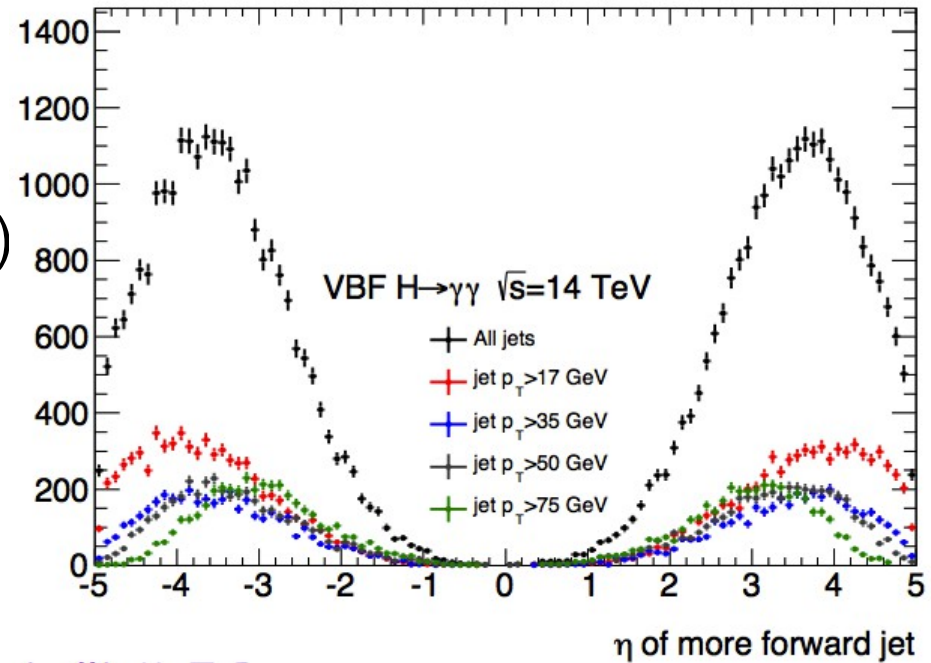
Future plans

- USBPix is being modified to enable configuration only with USBPix/STControl
 - makes implementation of scans much easier
 - will probably enable sub-pixel disentanglement for the whole matrix without the need for pixel-by-pixel analysis
- further submissions are being discussed
 - one ATLAS/CLIC submission in November
 - array of $25 \times 25 \mu\text{m}$ pixels for the CLICpix demonstrator (only preamps)
 - in addition 6 different versions of rad-hard pixel circuits for trials
 - some R&D structures: direct n-well access for eTCT, test transistors, ...
 - for comparison: area only $2.3 \times 2.8 \text{mm}$, cost $\sim 6.5 \text{ kEUR}$
 - dedicated to strip readout
 - optimised sub-strip pitch ($50 \mu\text{m}$? $25 \mu\text{m}$?) in combination with z-resolution
 - dedicated to disks
 - square pixels preferred
 - $50 \times 50 \mu\text{m}$ should be achievable with FE-I4
 - sensor candidate for “standard disks” and for very forward tracking

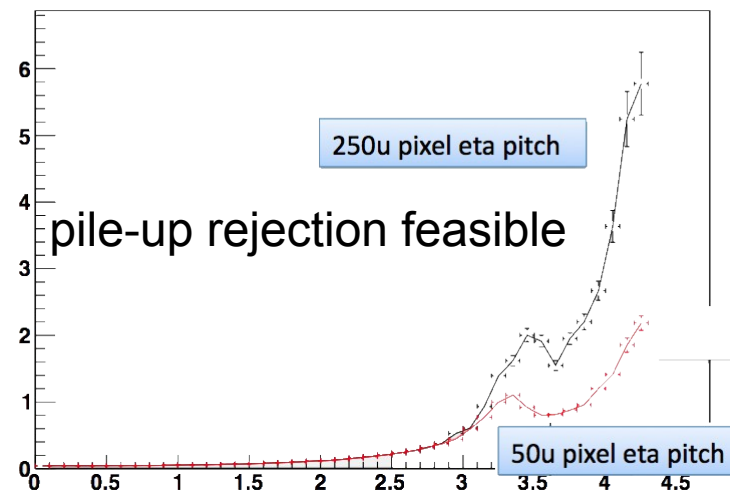
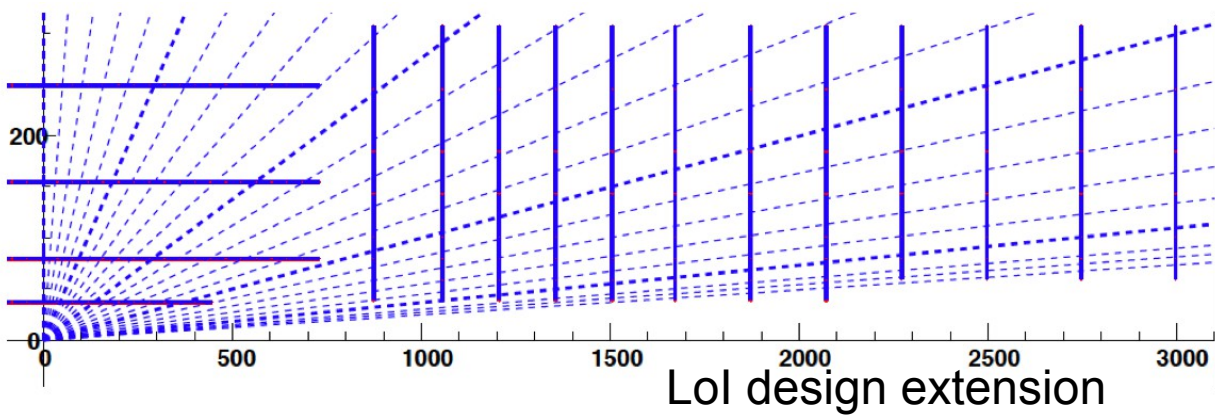


Case study: Very forward tracking

- Limitation to pseudorapidity of eta = 2.5 inappropriate wrt VBF/VBS
- Design studies ongoing for an extension to eta~4 (phase 2 upgrade)
 - physics: Higgs self-coupling, vector boson scattering
 - layout: acceptable area increase
 - sensor challenges: mass production, rad-hardness at small radii, square pixels/small eta pitch preferred → HV-CMOS?

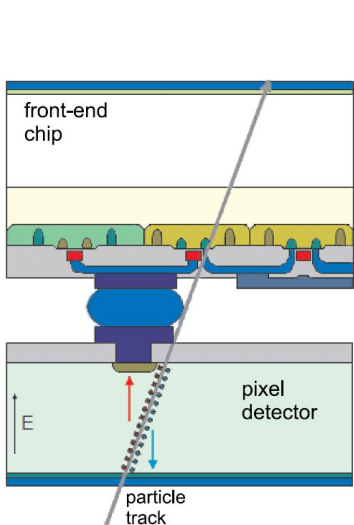


z0 resolution as a function of eta

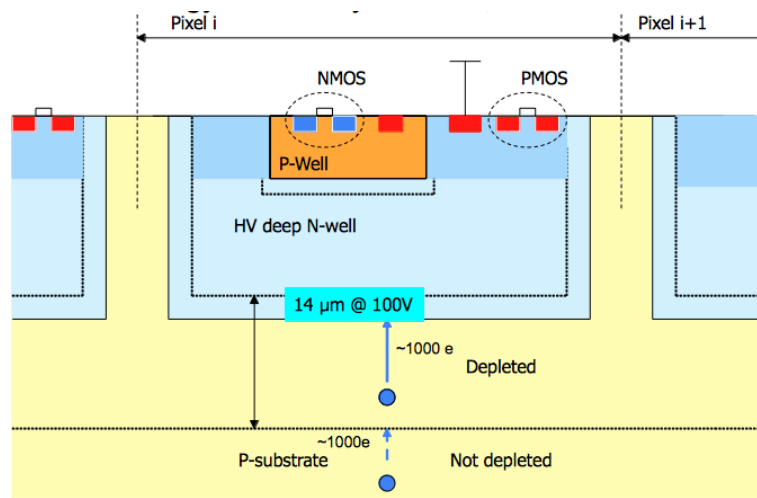


HR-CMOS

- As mentioned, main requirement for drift-based MAPS is a deep n-well
- Higher substrate resistivity would allow for full depletion
 - certainly larger initial signal, reduction of depletion depth to be studied
 - charge sharing possible again allowing to higher resolution at low fluences
- Several CMOS imager processes available from different foundries
 - back-side illumination requires full depletion and thin sensors
 - high-resistivity FZ base material available in an industrialised process
- First HR-CMOS efforts started at University of Bonn

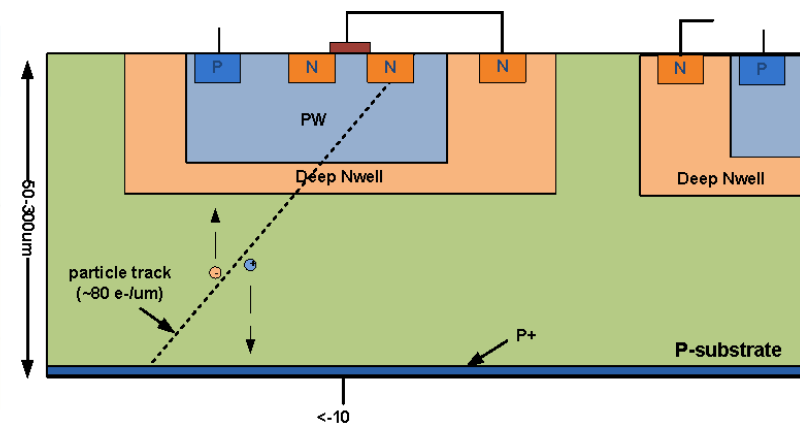


Hybrid



CMOS electronics placed inside the diode (inside the n-well)

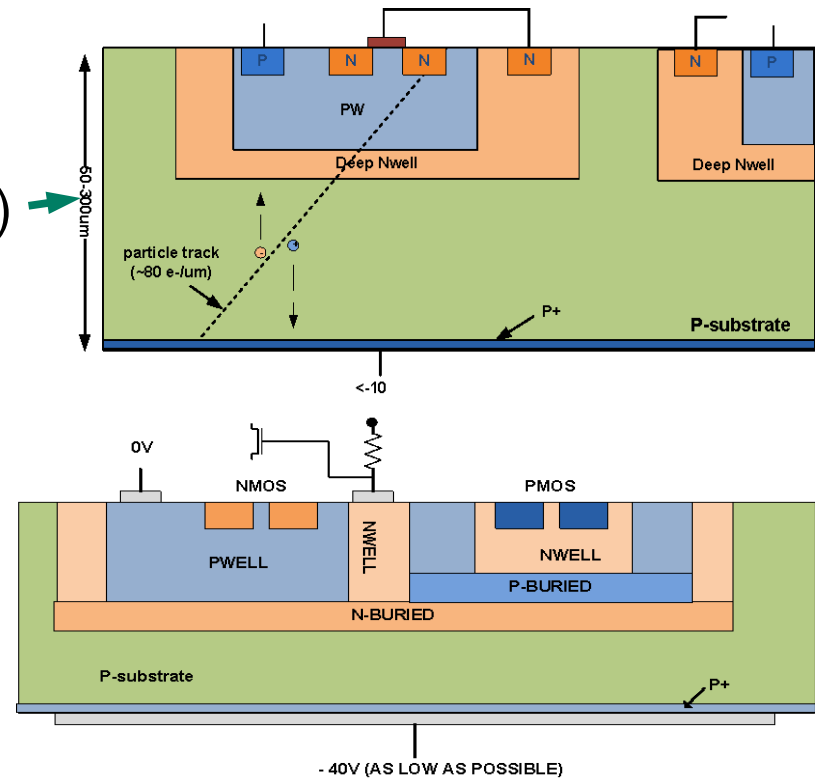
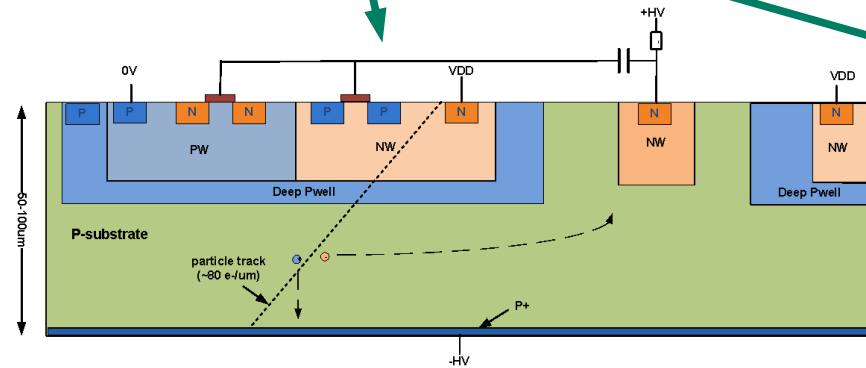
HV-CMOS



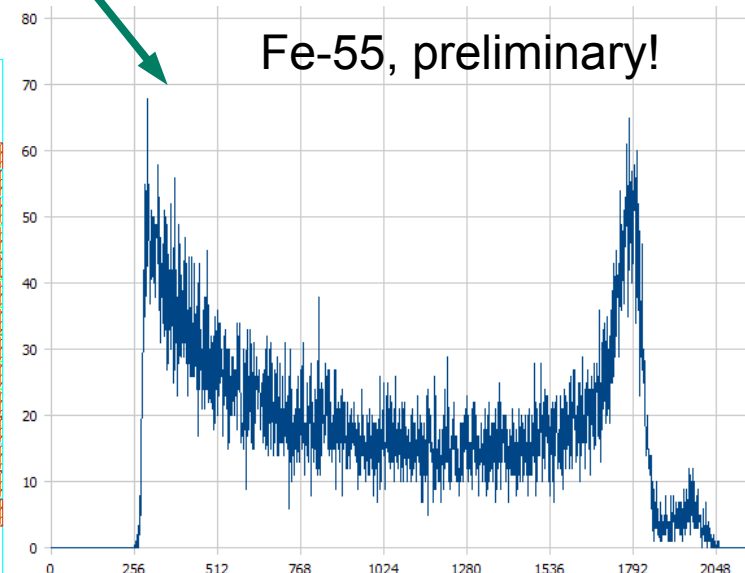
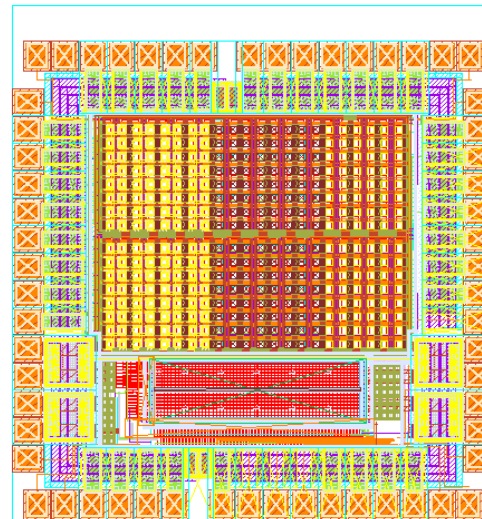
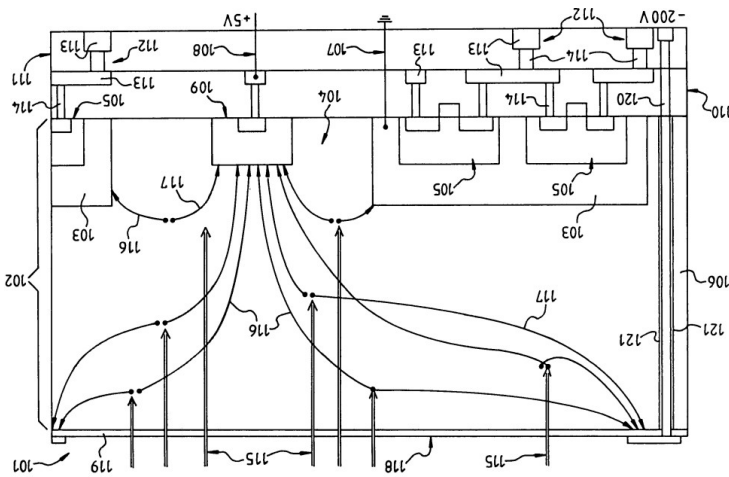
HR-CMOS

HR-CMOS

- Many different designs possible:
 - HV-CMOS like (deep n-well, no triple-well)
 - triple-well
 - Alice-like



- First prototypes back from ESPROS, see physics
 - characterisation, irradiations to follow



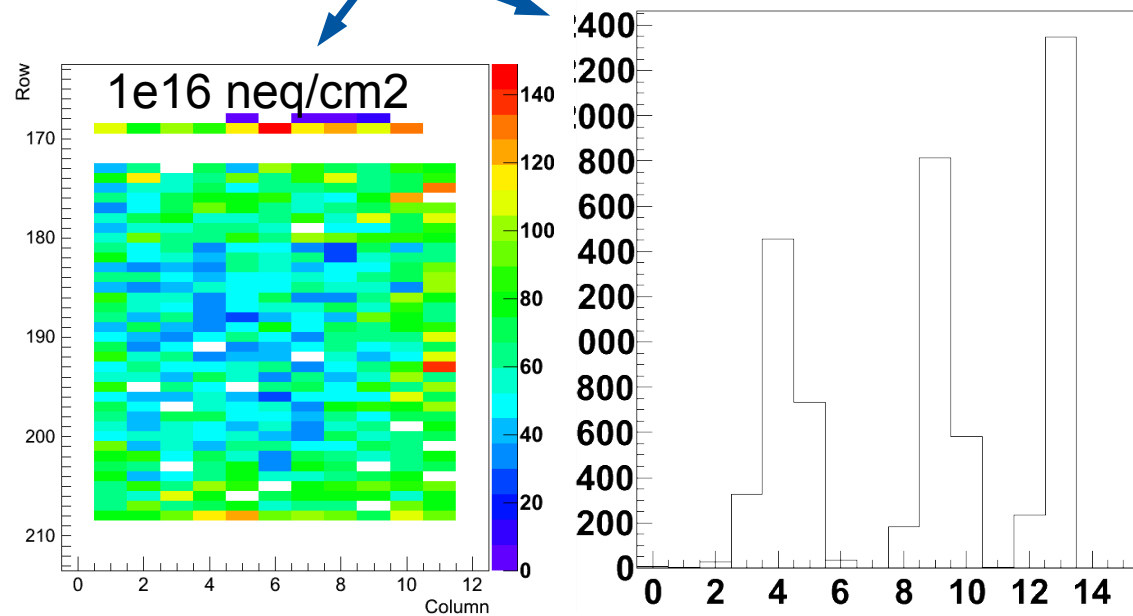
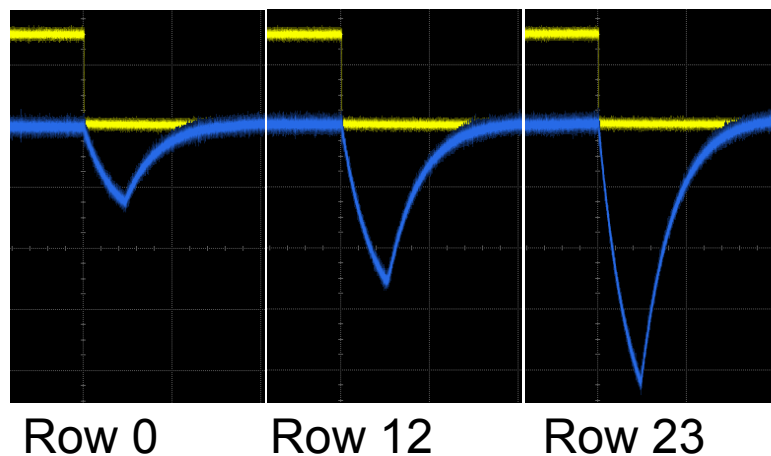
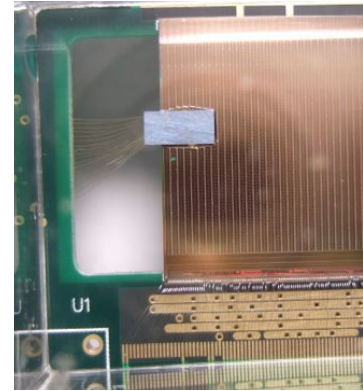


(HV-)CMOS and RD50

- It has been proposed to cover (HV-)CMOS within RD50
- I'd like to support this idea:
 - CMOS developments up to now driven by chip design institutes
 - lack of bulk (damage) knowledge
 - CMOS sensors are n-in-p pixel sensors, often on Cz substrates
 - quite some background in RD50
 - Many current developments rely on test systems/readout chips/methods well known within the RD50 community
 - Test chip productions well suited for RD50
 - fast turnaround (3-6 months, depending on foundry)
 - small test chips cheap (well below 10kEUR)
 - many flavours to choose from
 - Radiation hardness with hybrid sensors has progressed well, now it might be the time to look into
 - “affordable” solutions (also including low mass)
 - enhanced features: e.g. very fine-pitch, data reduction for industrial-pitch bump-bonding, ...

Conclusions

- HV/HR-CMOS processes might yield radiation-hard, low-cost, improved-resolution, low-bias-voltage, low-mass sensors
- Process can be used for
 - “classical” passive n-in-p sensors
 - 'active' n-in-p sensors (with capacitive coupling)
 - drift-based MAPS chips
- First prototypes being explored
 - very first HR-CMOS measurements encouraging
 - results with capacitively coupled HV-CMOS pixel sensors look promising
 - “virtual” strip sensors – z-position encoding works

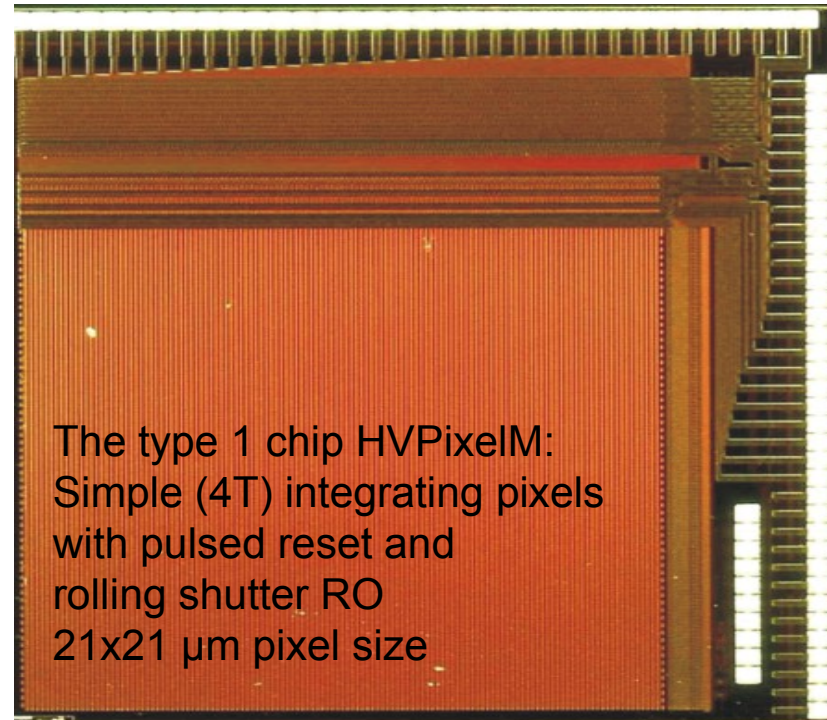




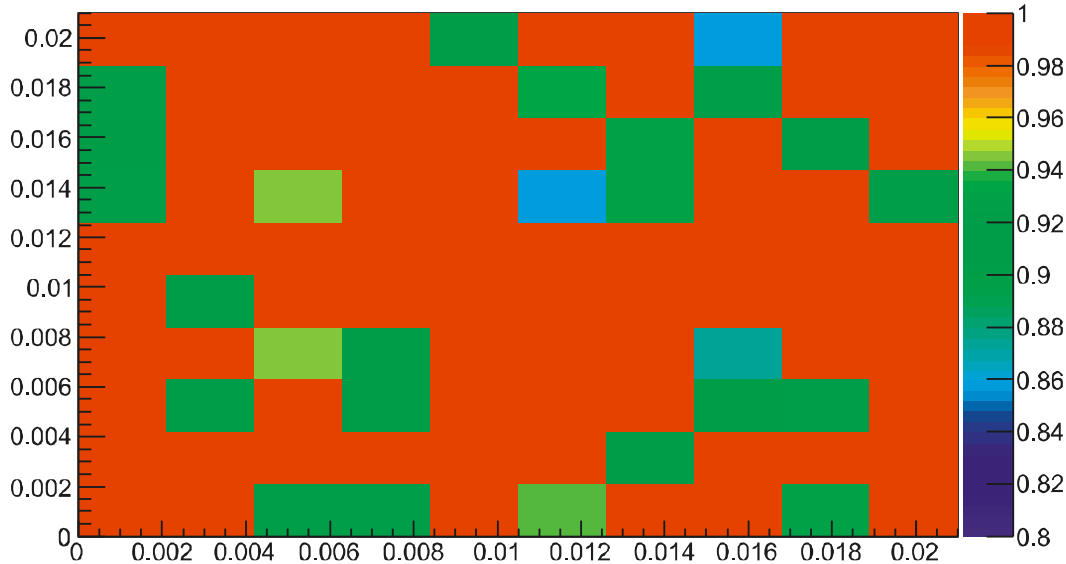
Backup slides

Test beam results: monolithic

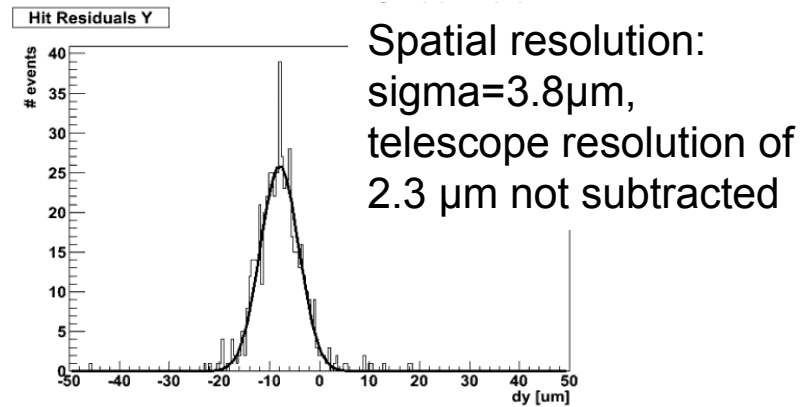
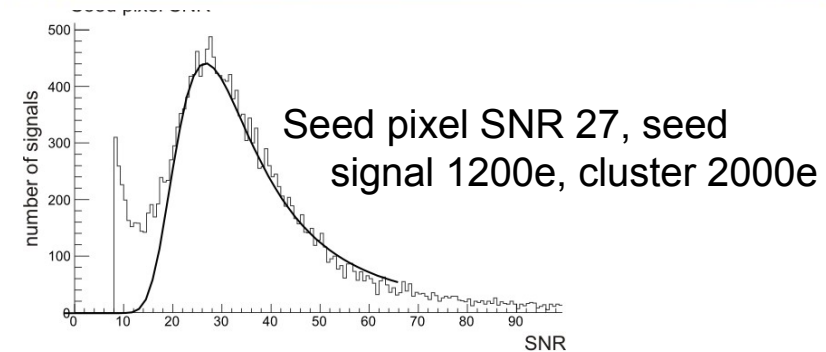
- excellent resolution
- very good S/N ratio
- efficiency limited by readout artifacts:
 - column-based readout
 - row not active during readout
 - data analysis did not correct for this
 - very small chip → low statistics



Efficiency vs subpixel particle position in X/Y

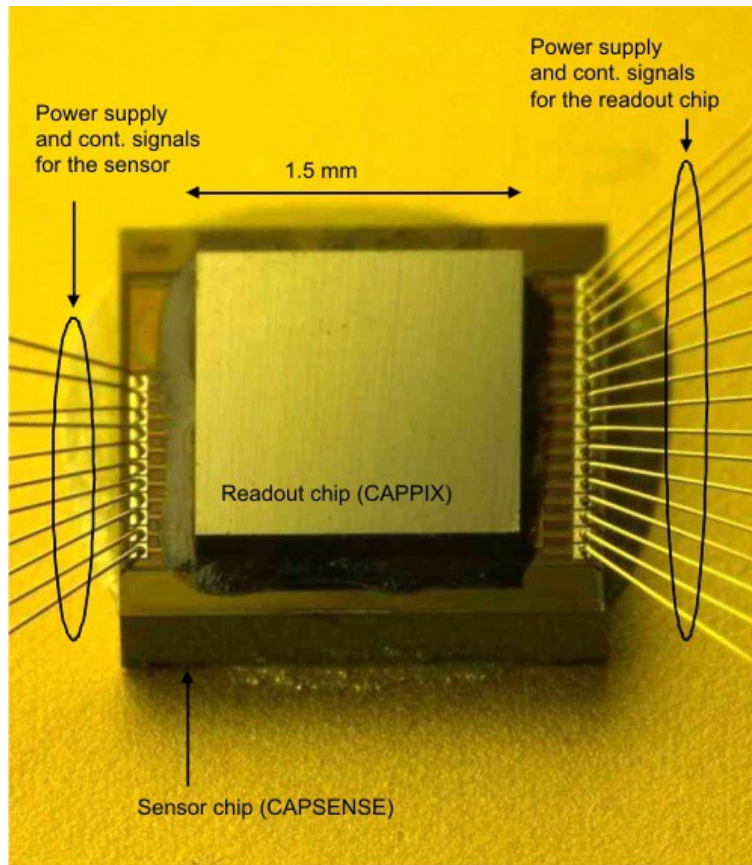


Efficiency vs. the in-pixel position of the fitted hit.
Efficiency at TB: ~98% (probably due to a rolling shutter effect)

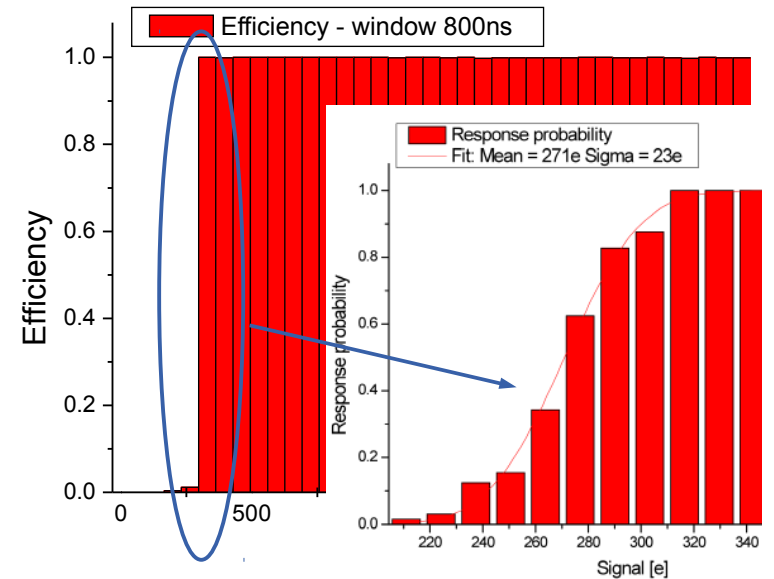


CCPD prototype results

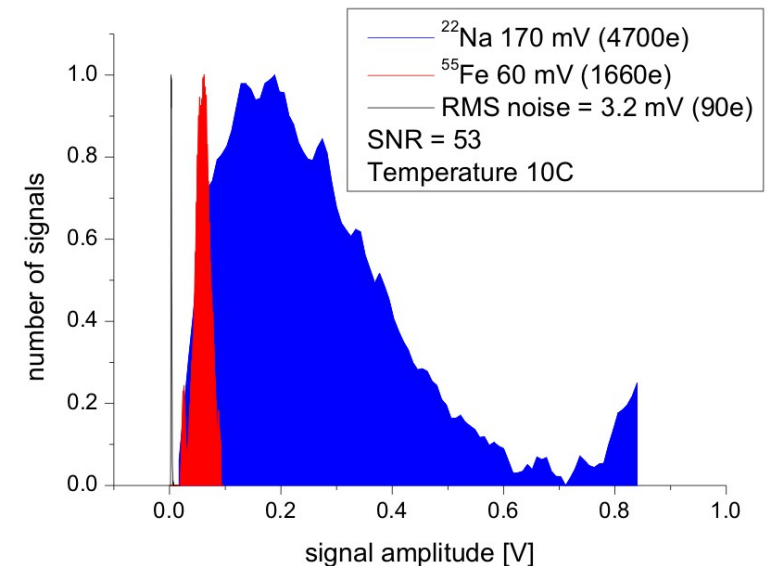
- excellent noise behaviour: stable threshold at ~ 330 electrons
- good performance also after irradiation



CAPPIX/CAPSENSE edgeless CCPD
50x50 μm pixel size



Detection efficiency vs. amplitude
Detection of signals above 330e possible with >99% efficiency.



Signals and noise of a CAPSENSE pixel after $10^{15} \text{n}_{\text{eq}}/\text{cm}^2$

CPPD prototype results

- Irradiation with 23 MeV protons: 1×10^{15} neq/cm², 150MRad
- FE-55 performance recovers after slight cooling

